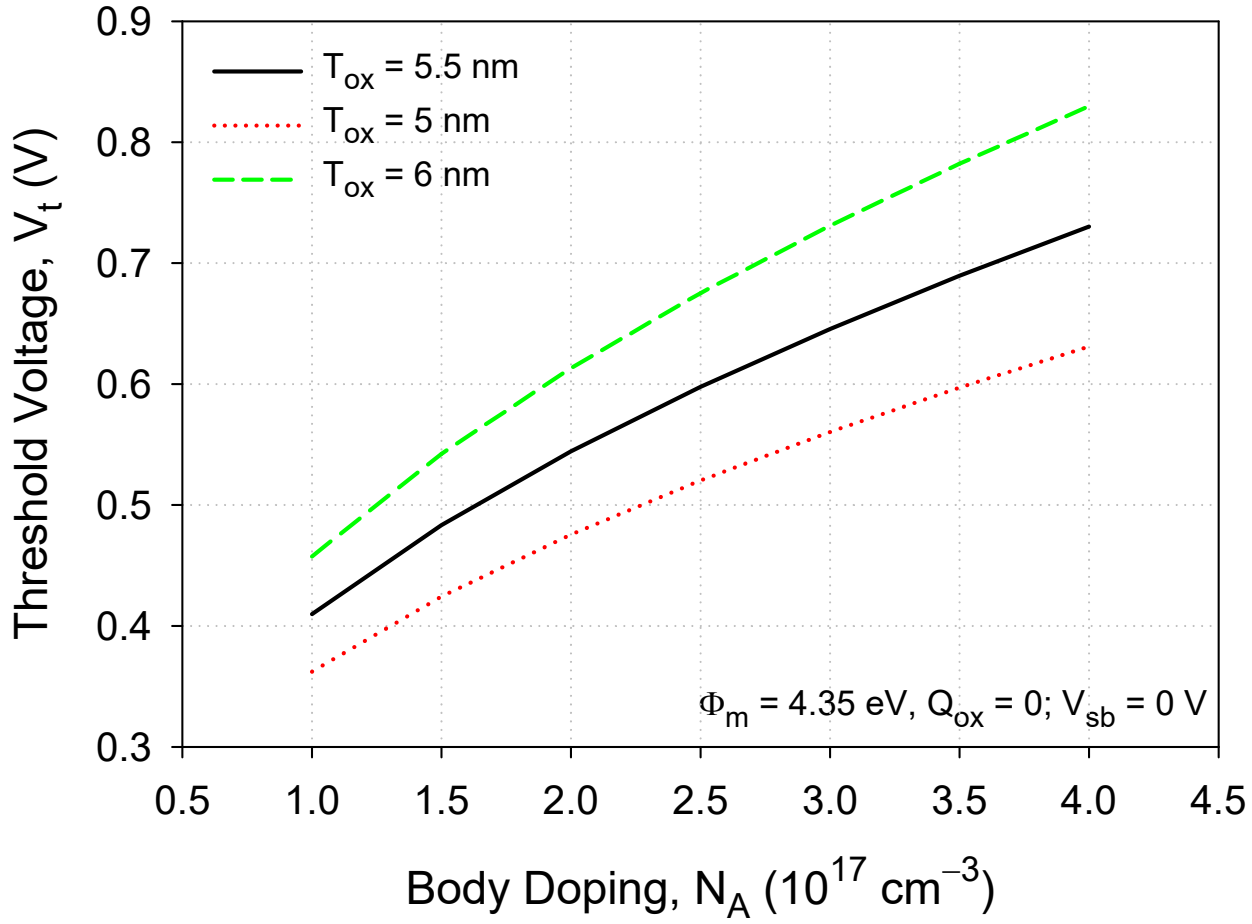
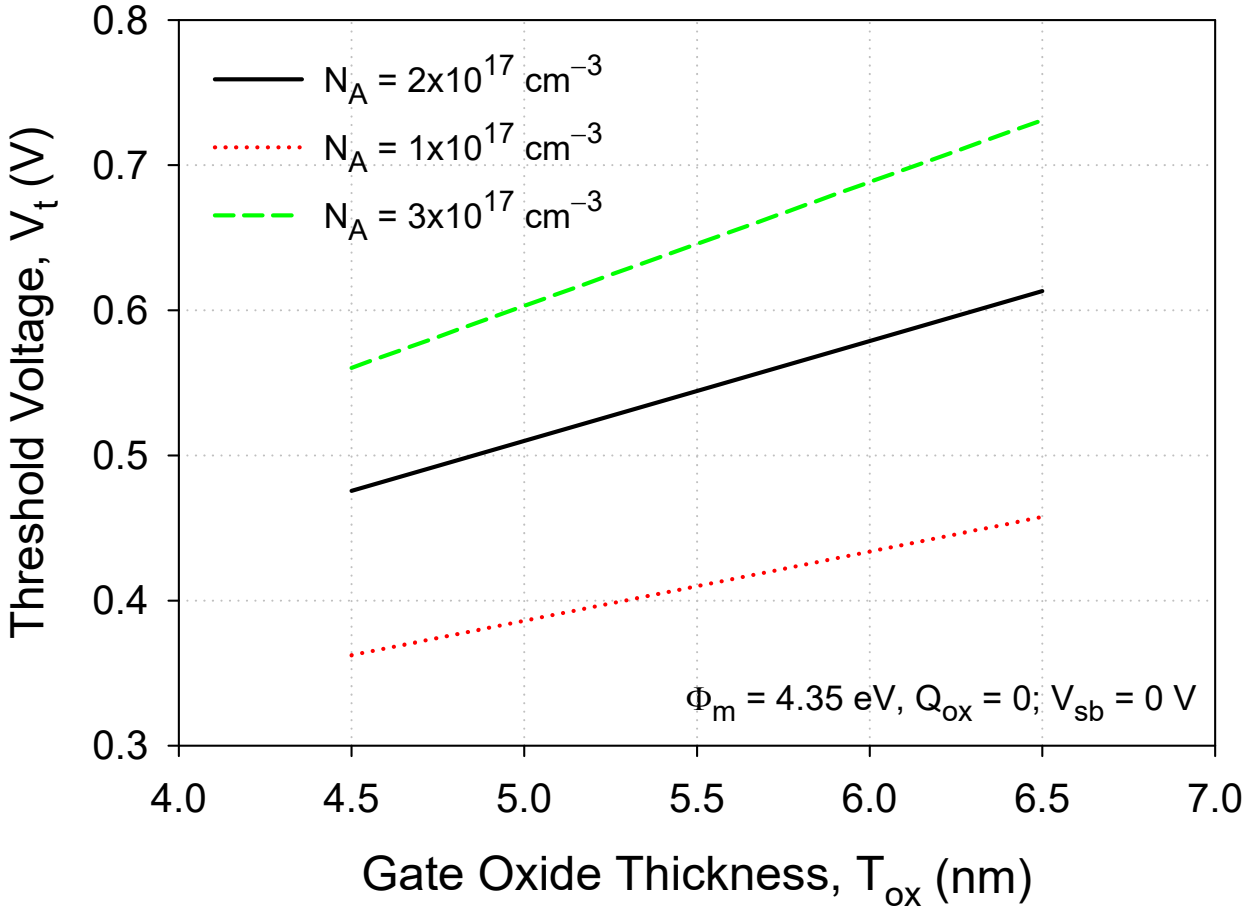
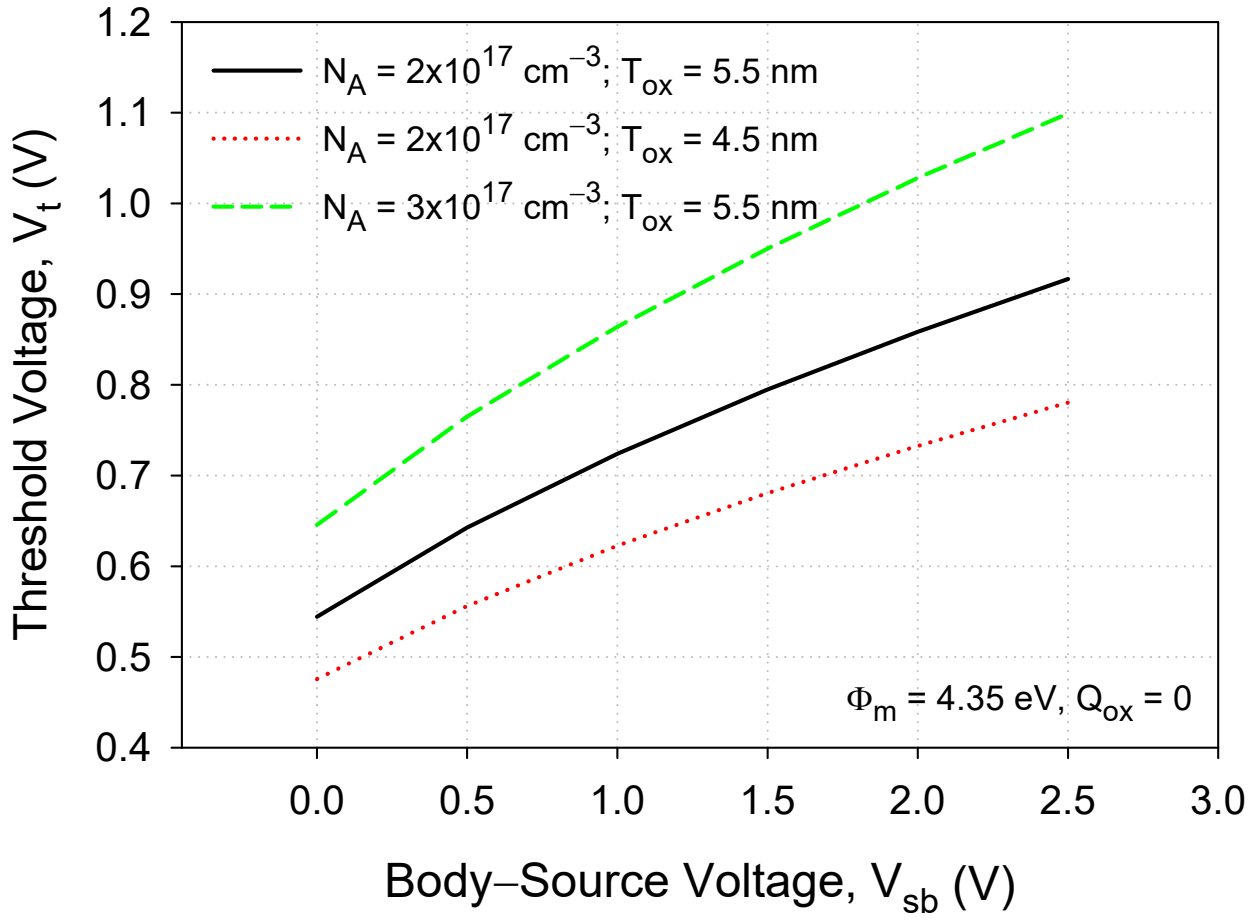
V_t vs. N_A at Various T_{ox}



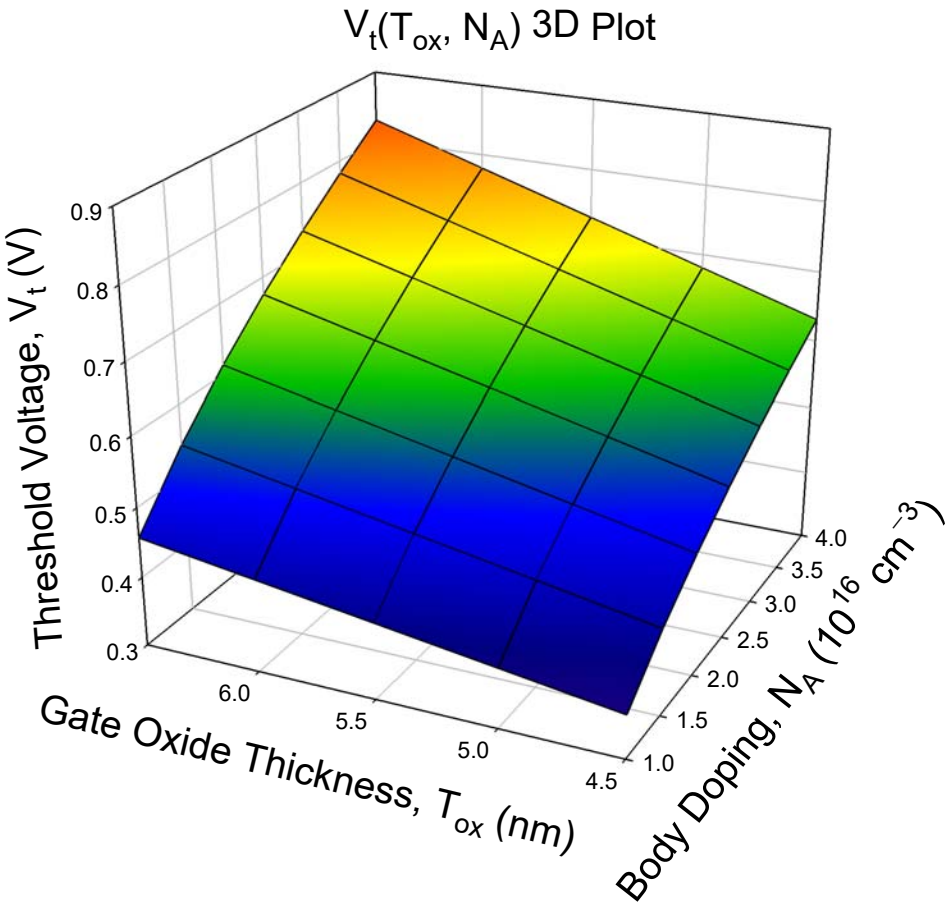
V_t vs. T_{ox} at Various N_A



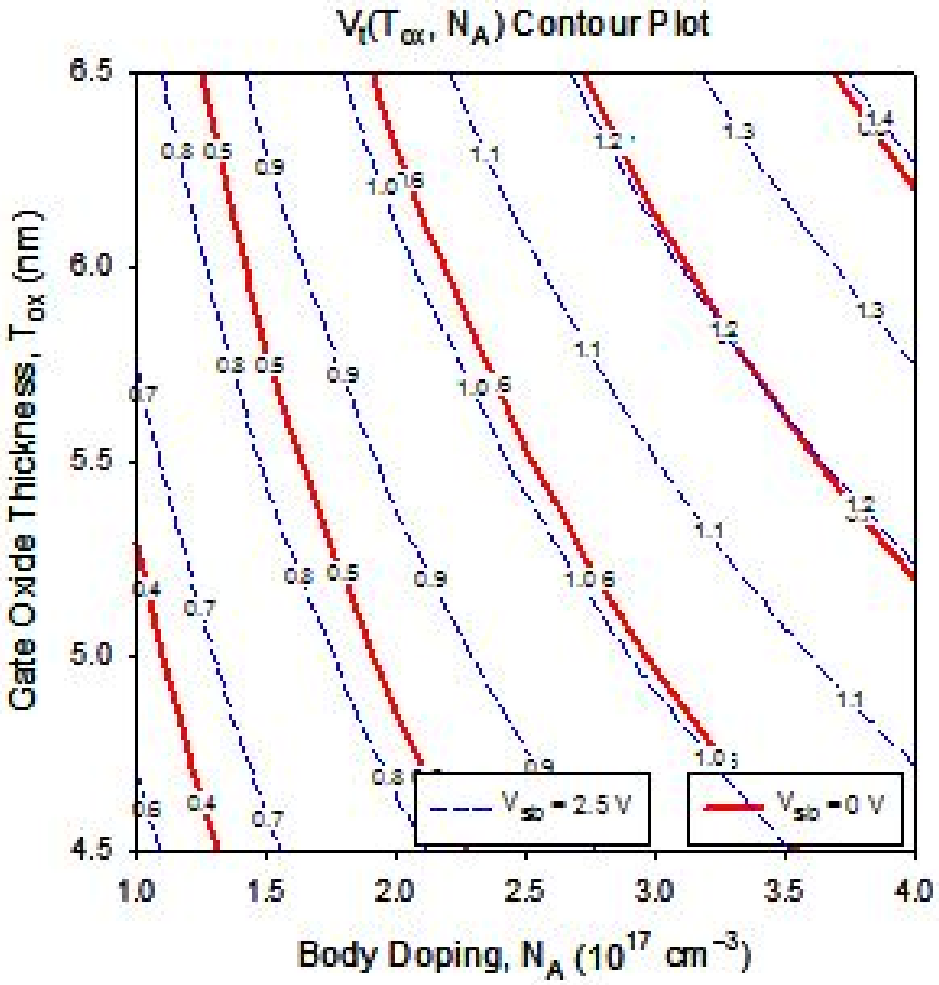
V_t vs. V_{sb} at Various N_A and T_{ox}



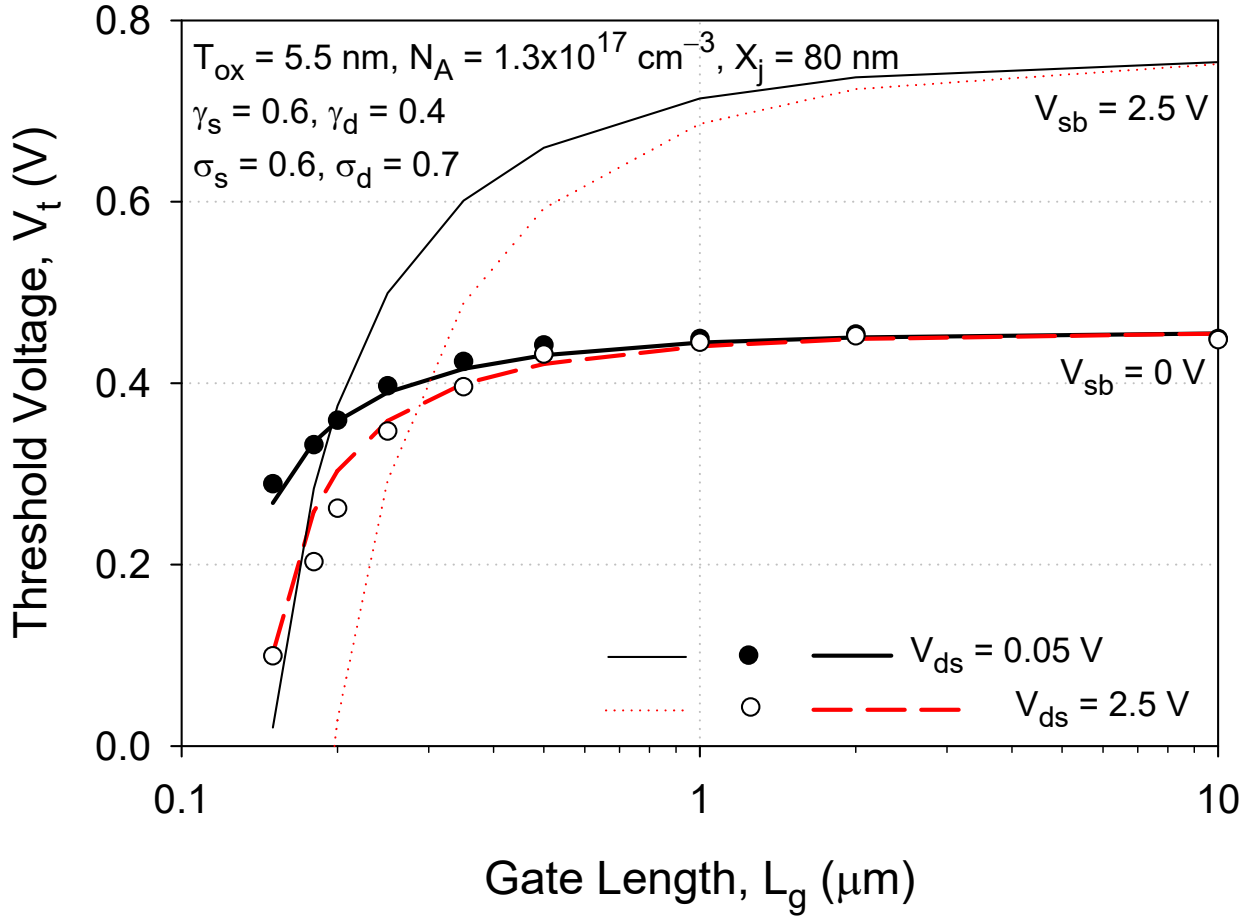
3D Plot: V_t vs. N_A and T_{ox}



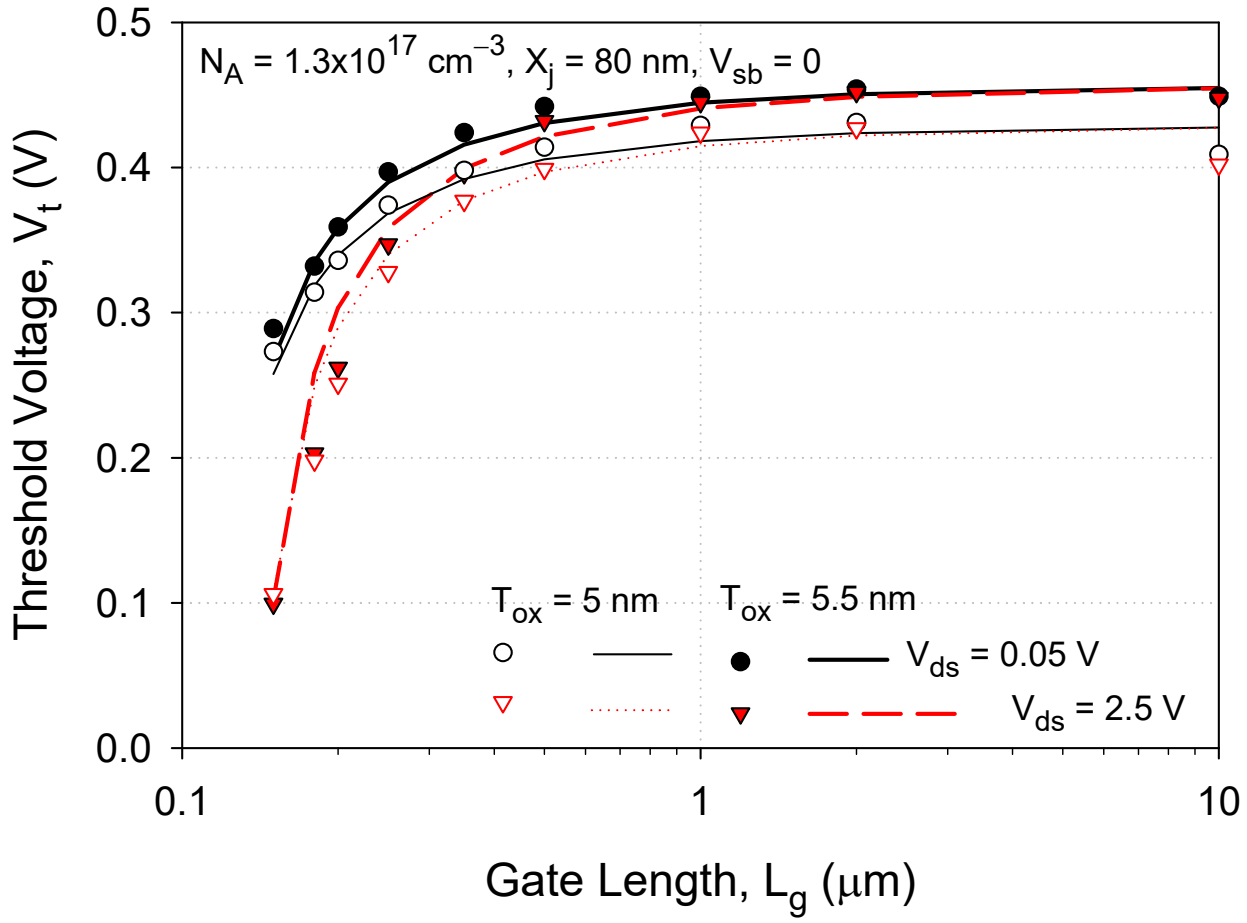
Contour Plot: V_t vs. N_A and T_{ox}



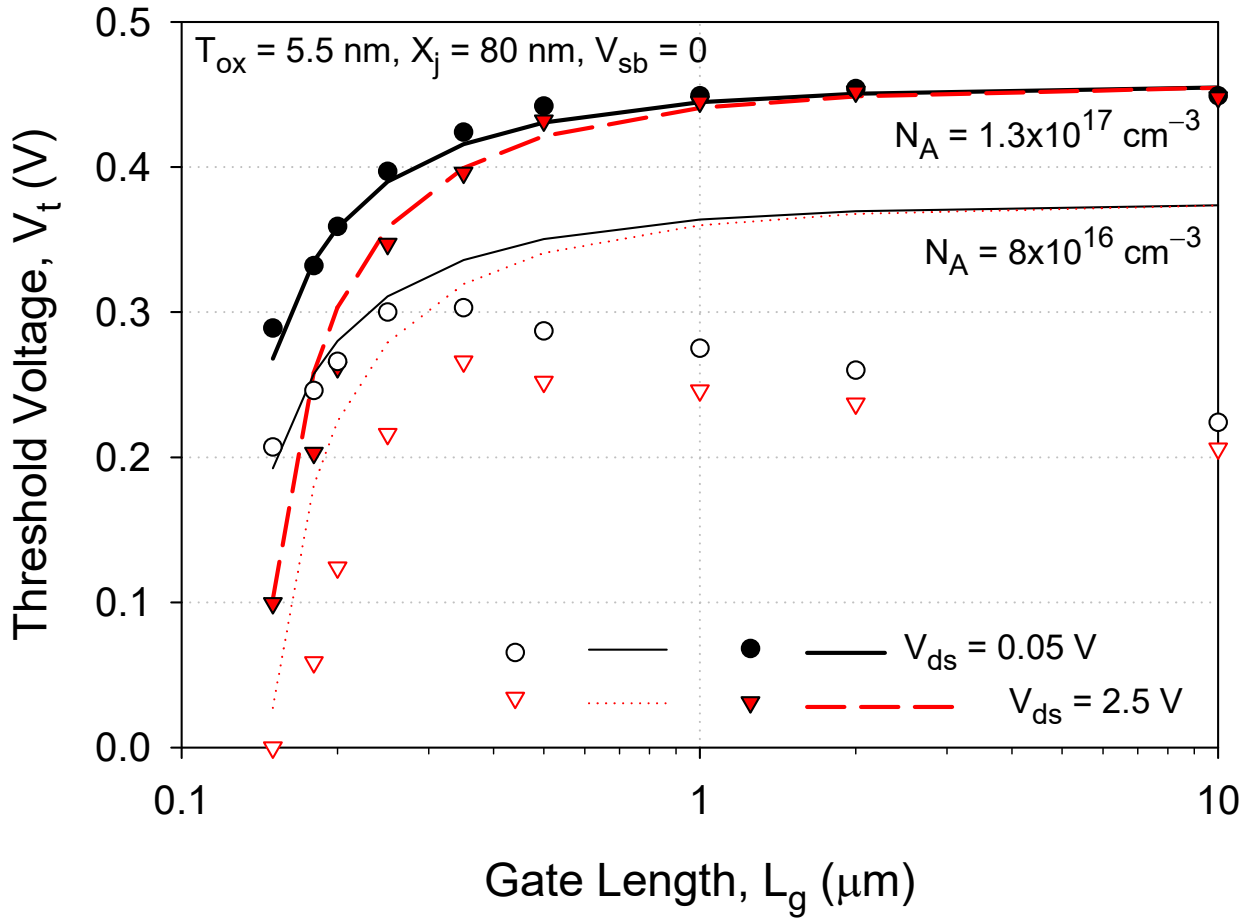
V_{t0} and V_{ts} vs. L_g at V_{sb} = 0 and 2.5 V



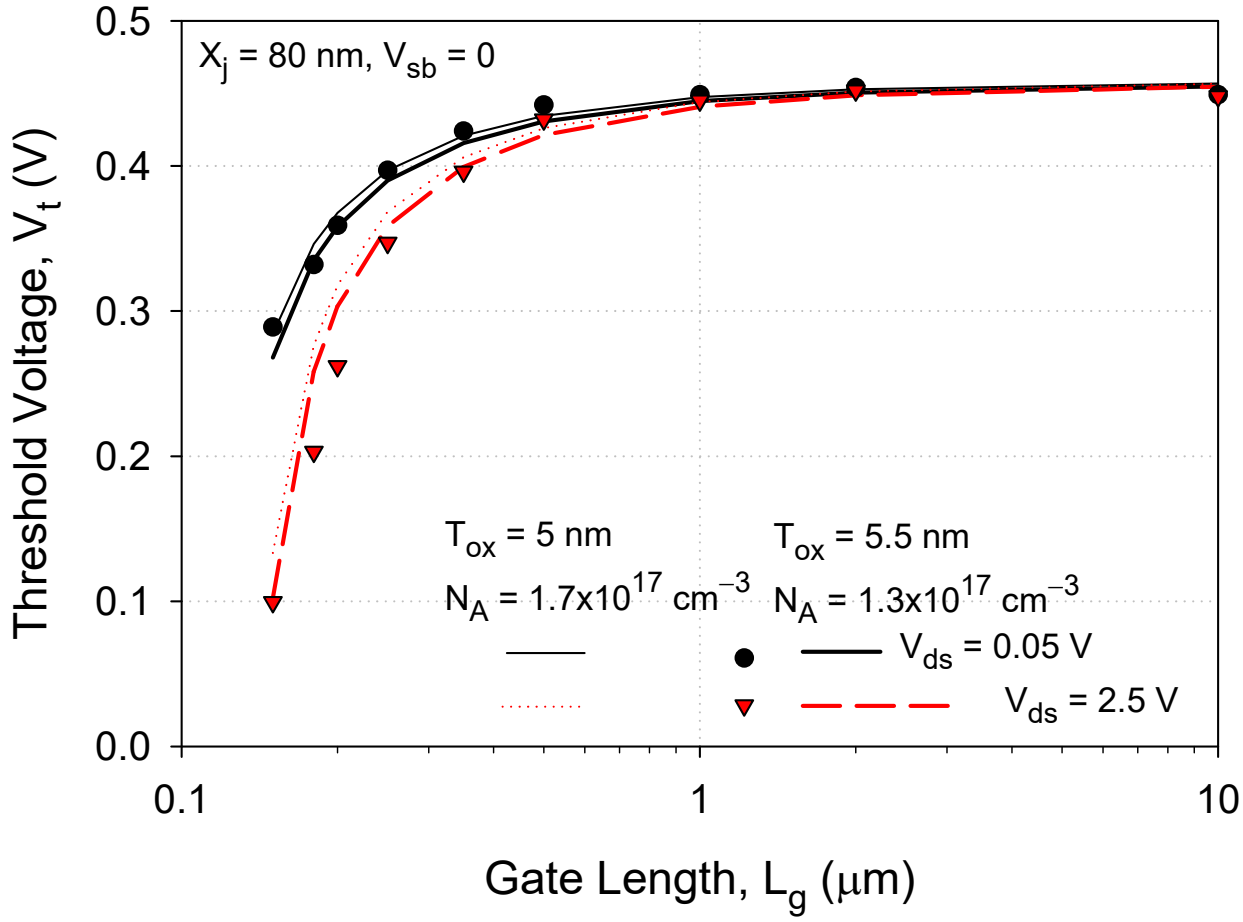
V_{t0} and V_{ts} vs. L_g at T_{ox} = 5.5 and 5 nm



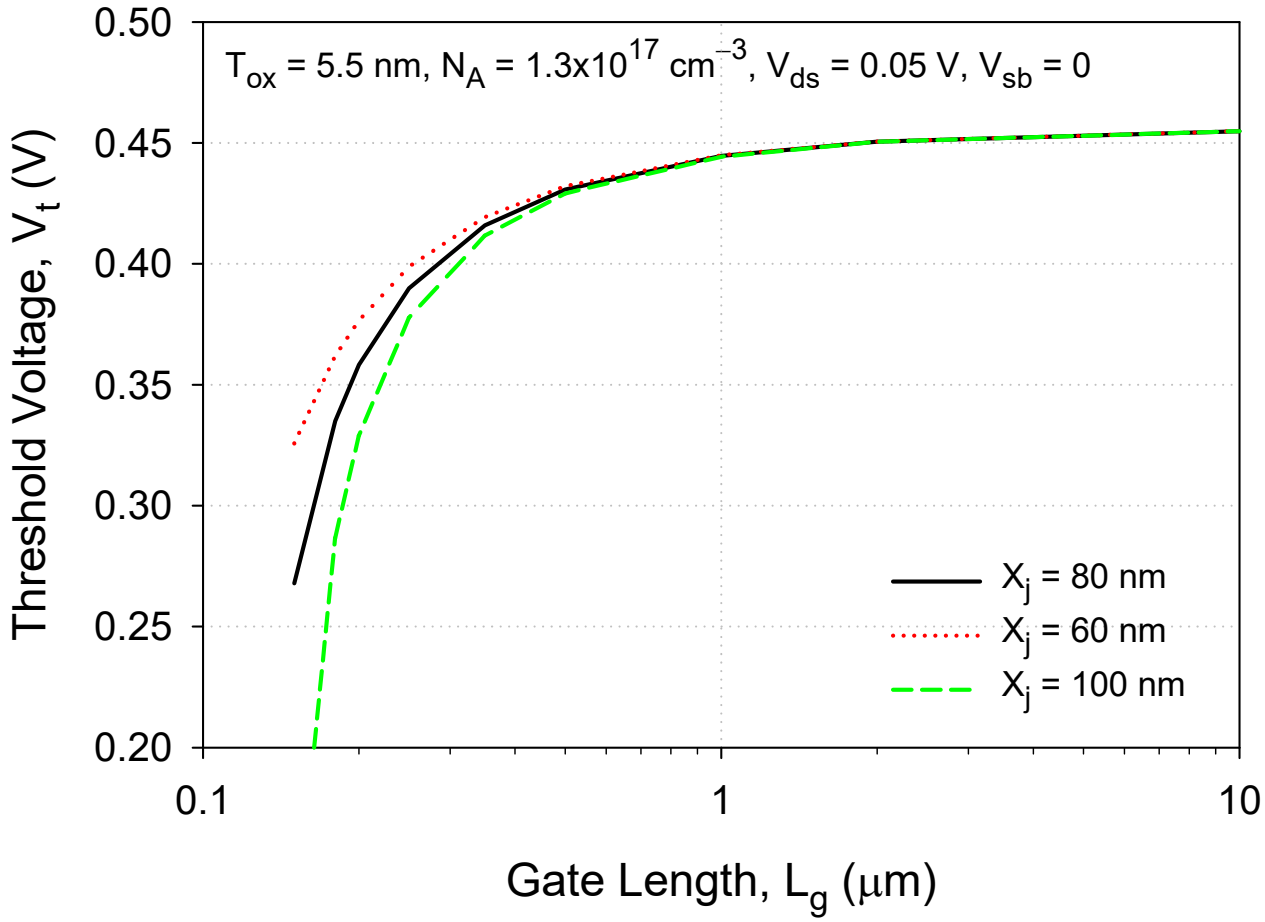
V_{t0} and V_{ts} vs. L_g at $N_A = 1.3x10^{17}$ and $8x10^{16}$ cm^{-3}



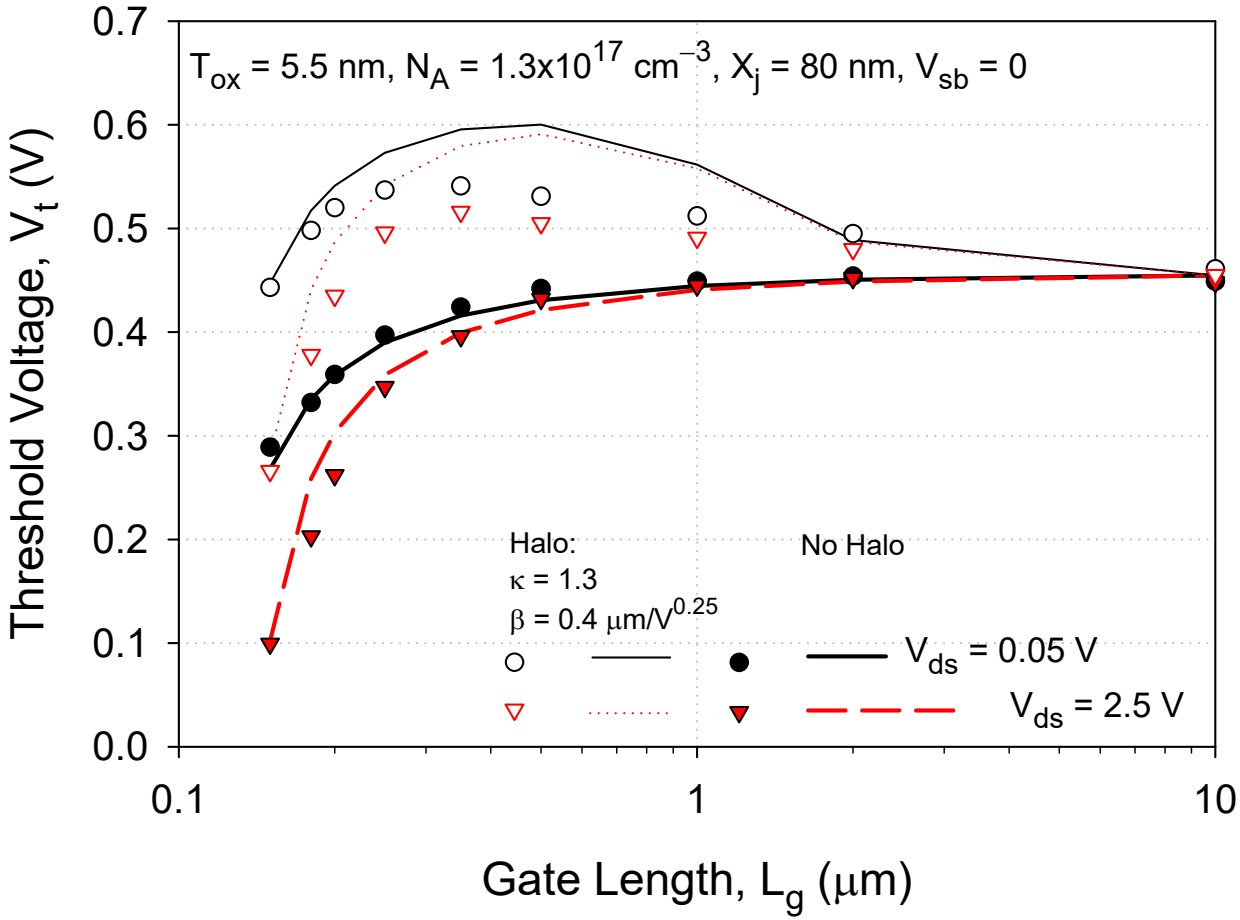
V_{t0} and V_{ts} vs. L_g at Two Pairs of N_A and T_{ox}



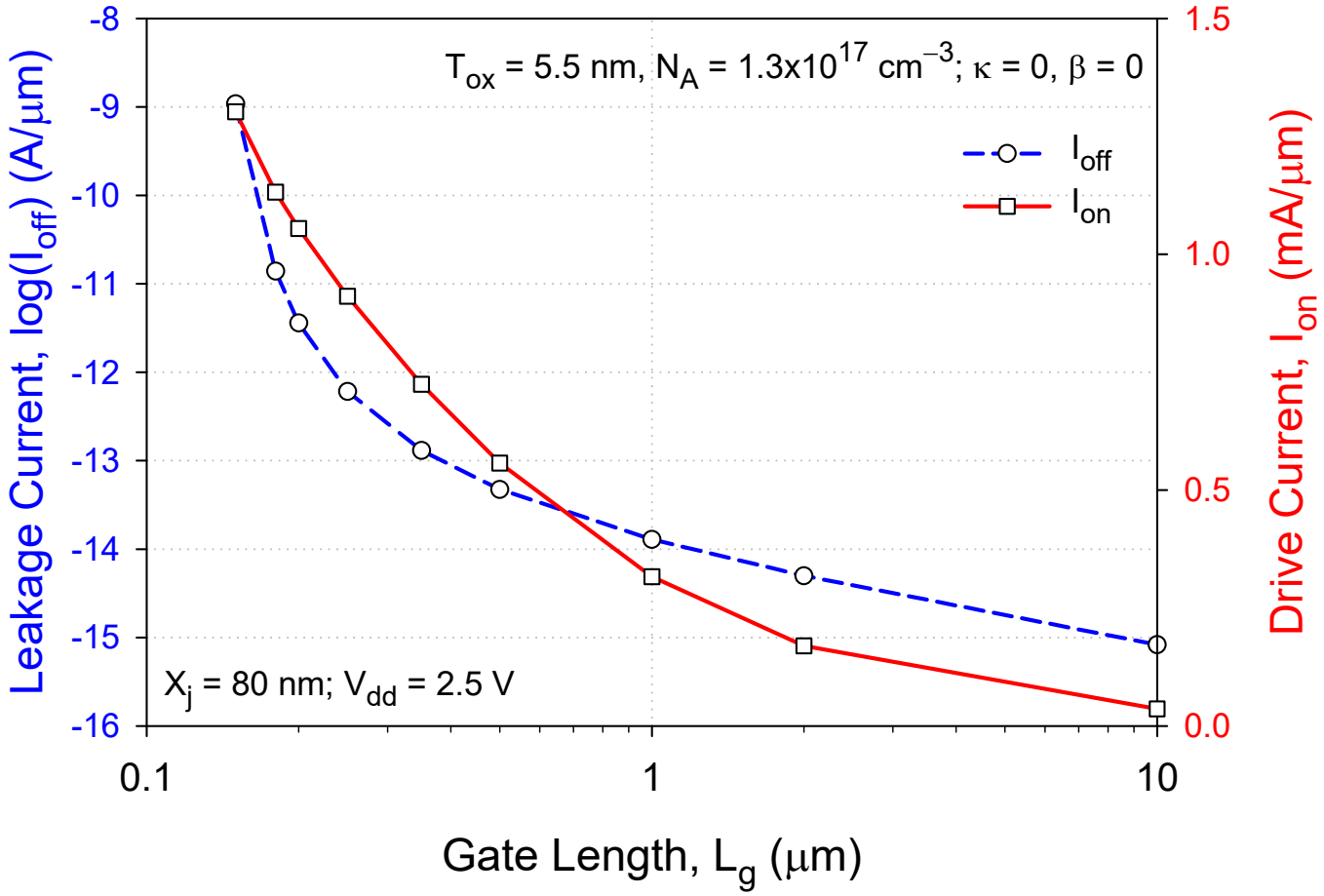
V_{t0} vs. L_g for Three X_j



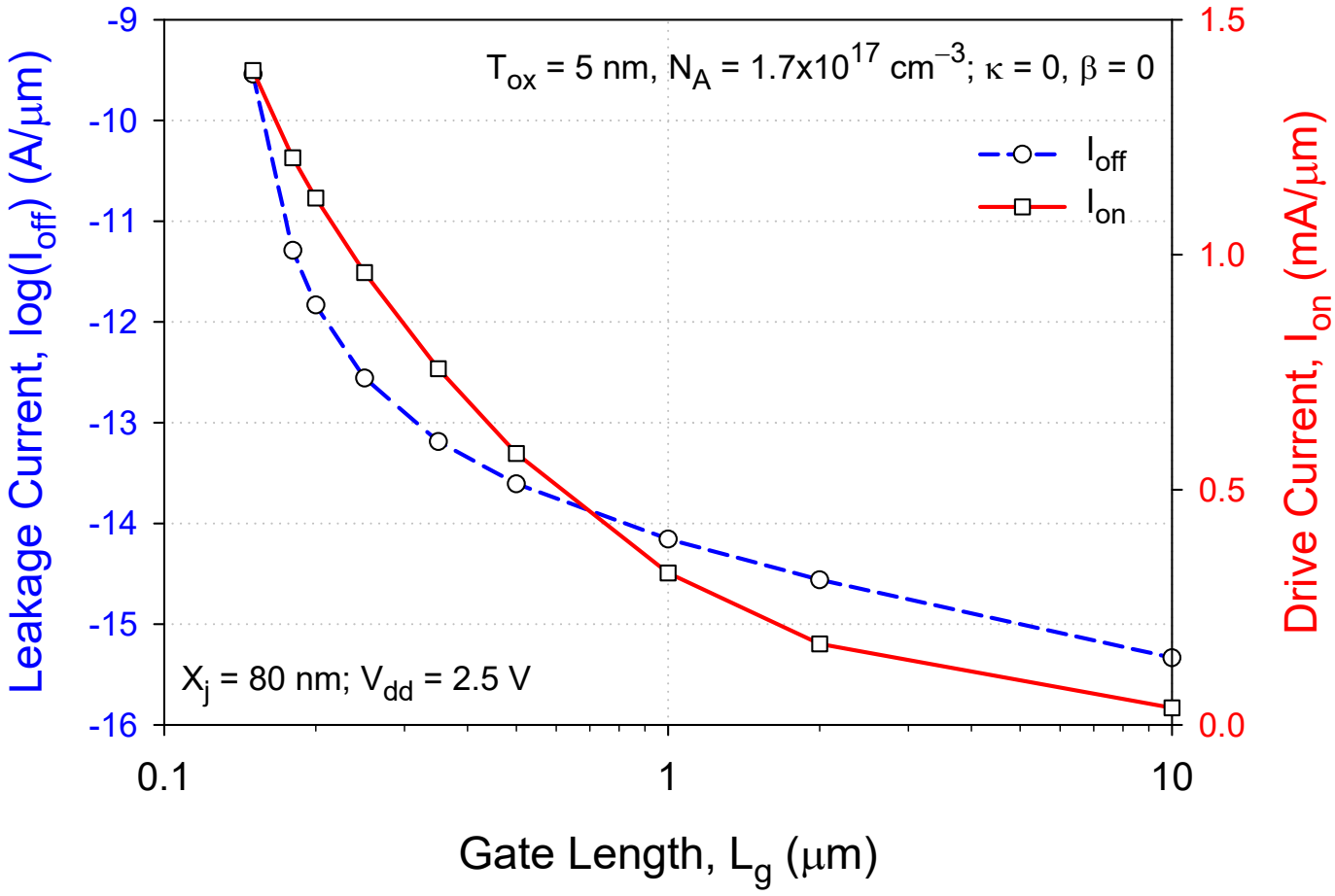
V_{t0} and V_{ts} vs. L_g at With and Without Halo



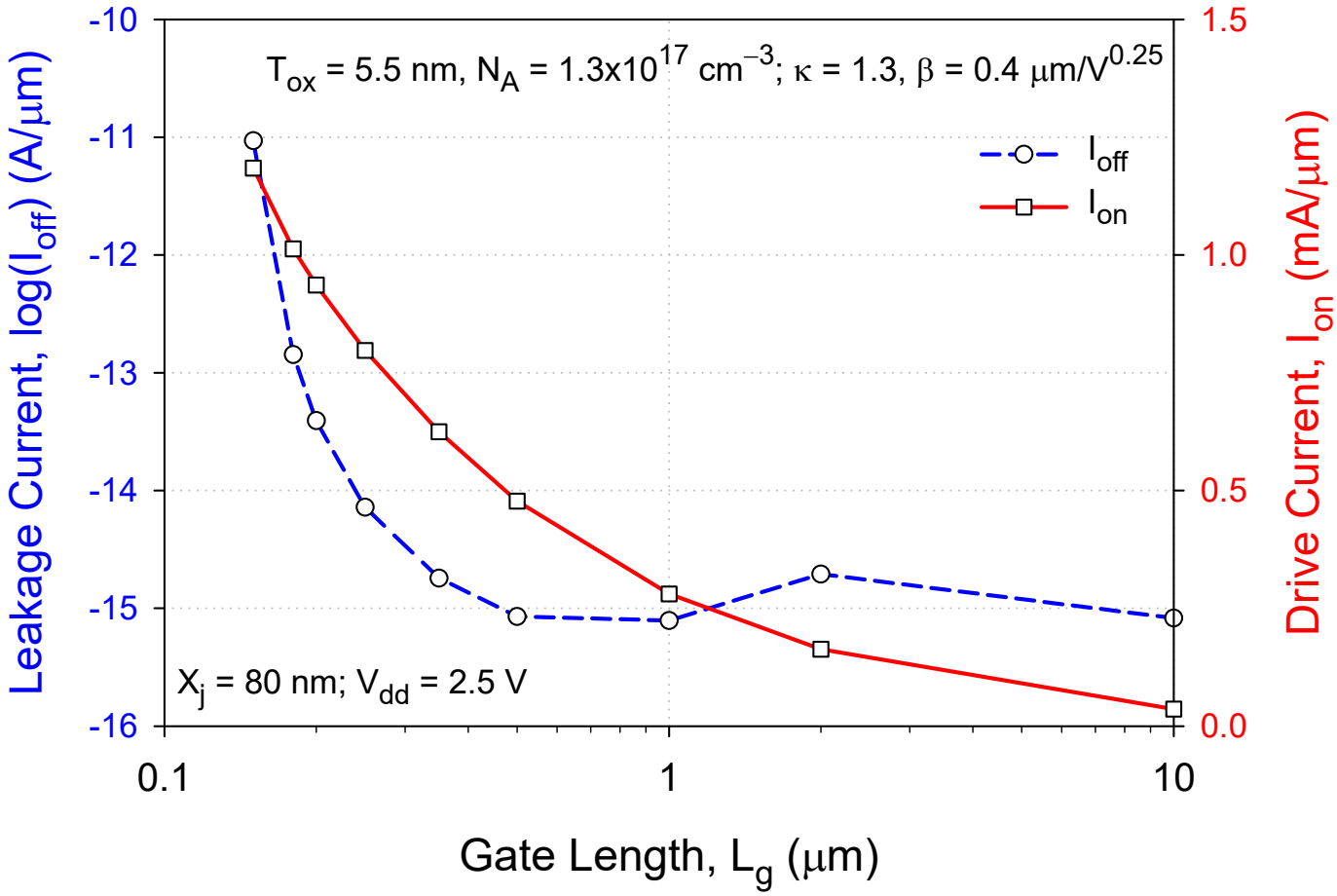
I_{on} and I_{off} vs. L_g for the Nominal (No Halo)



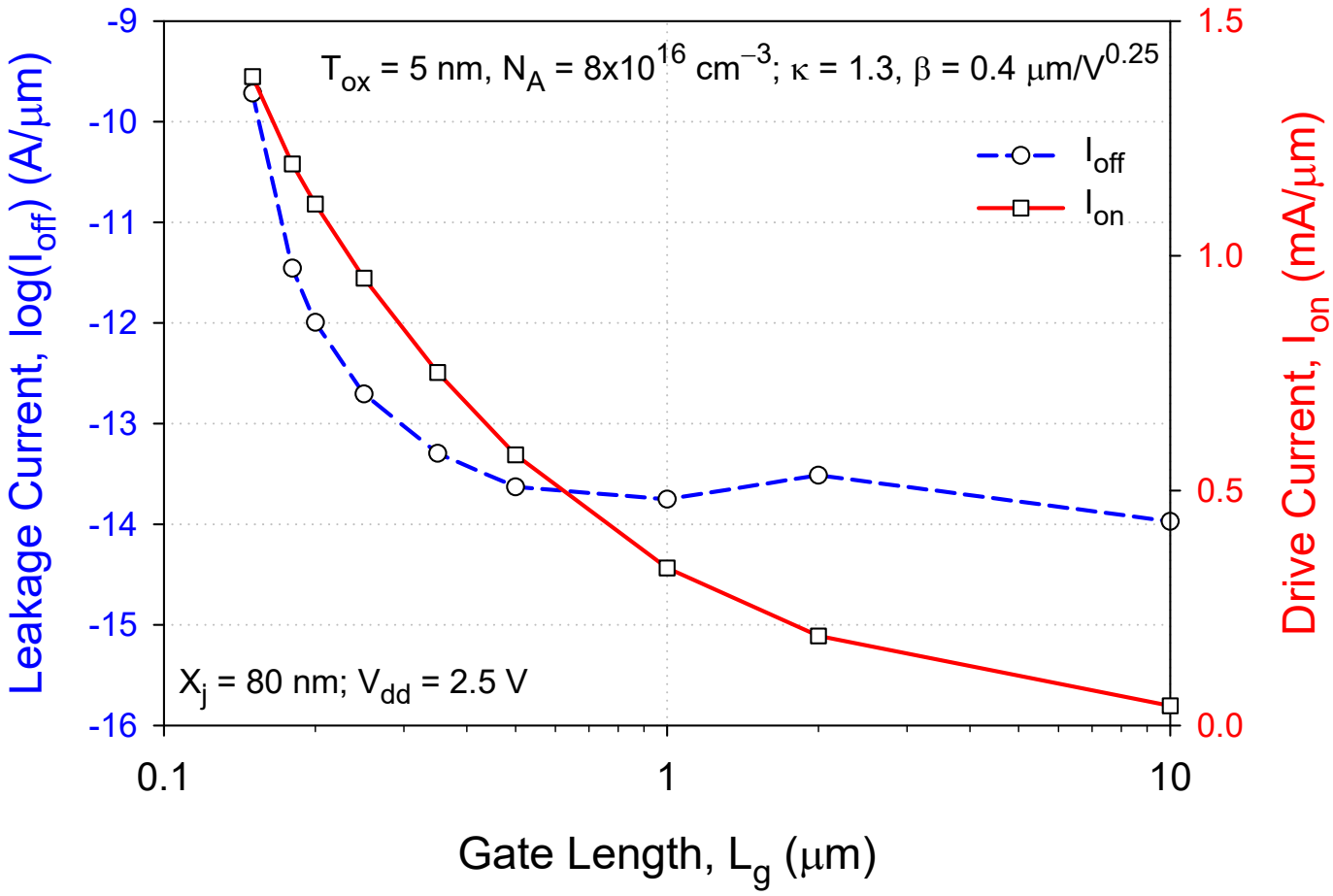
I_{on} and I_{off} vs. L_g at New T_{ox} and N_A



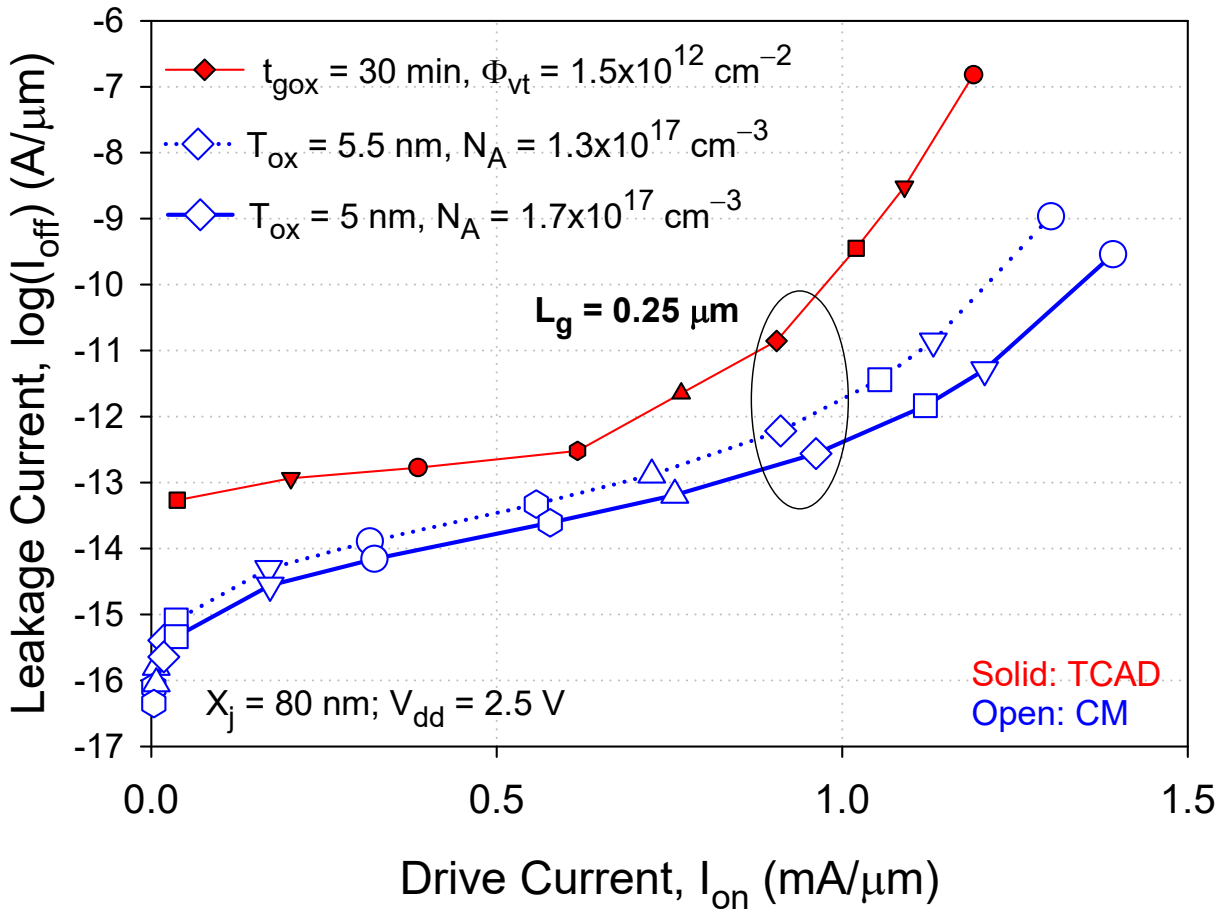
I_{on} and I_{off} vs. L_g for the Nominal (With Halo)



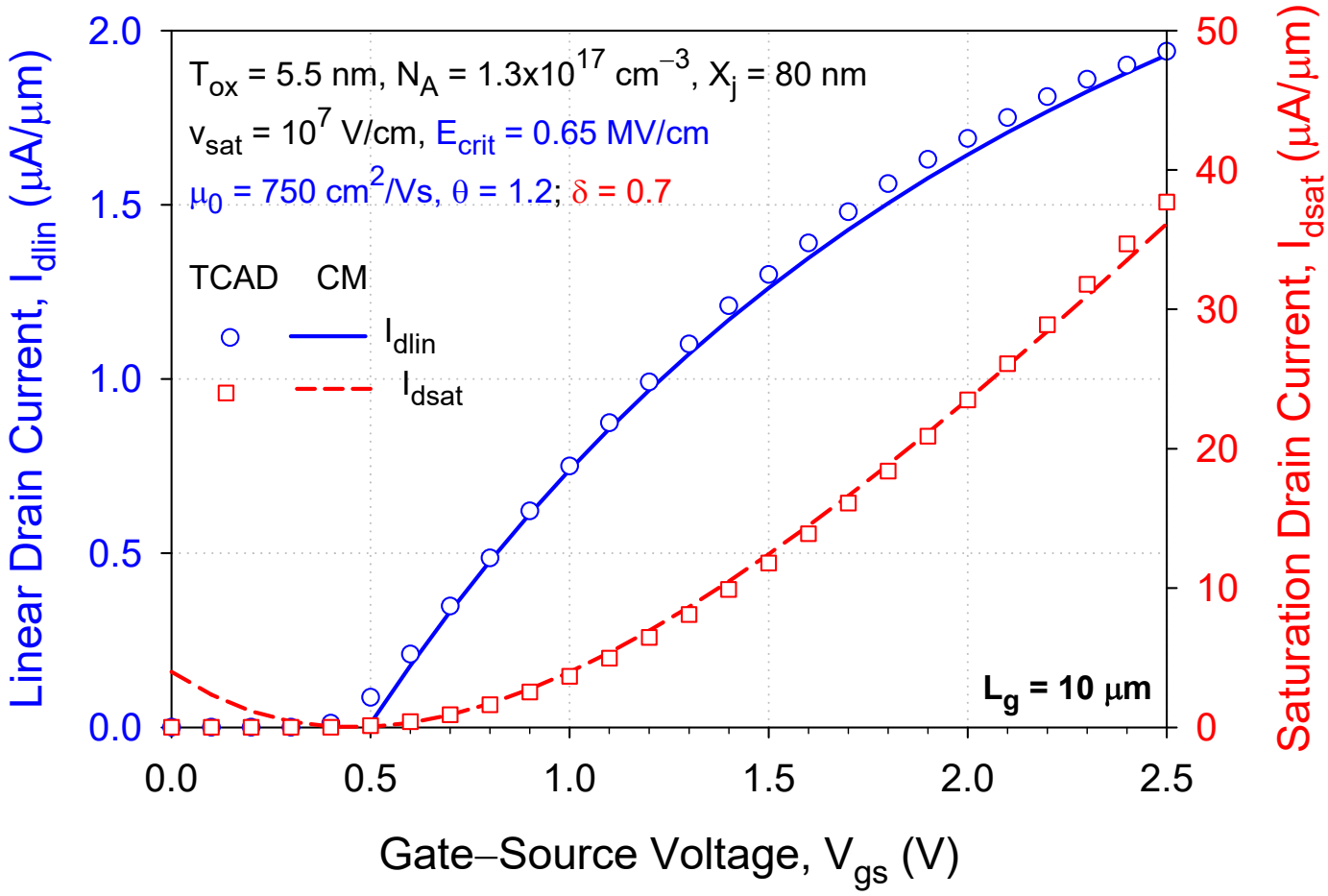
I_{on} and I_{off} vs. L_g at New T_{ox} and N_A with Halo



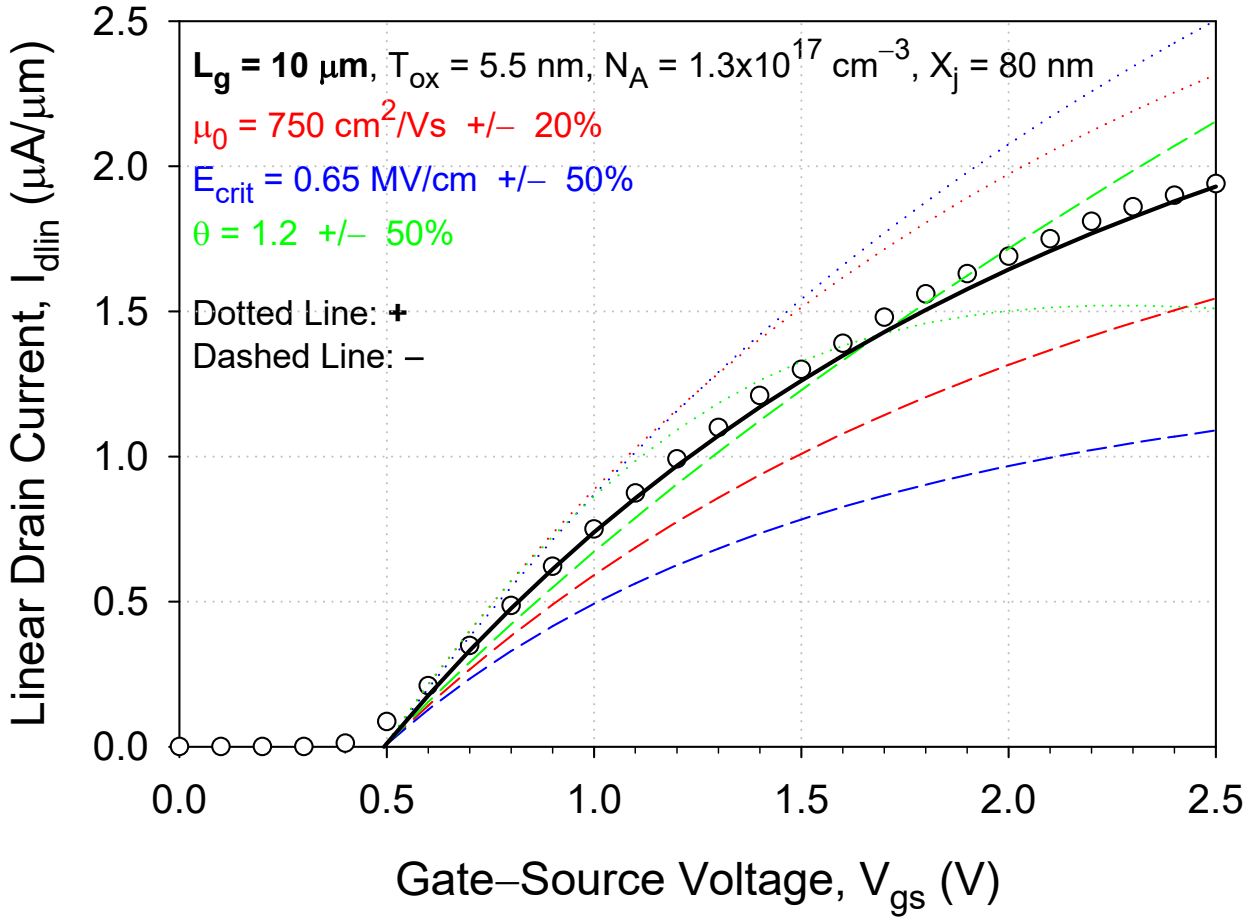
I_{off} vs. I_{on} at Various L_g for Nominal and New T_{ox} and N_A



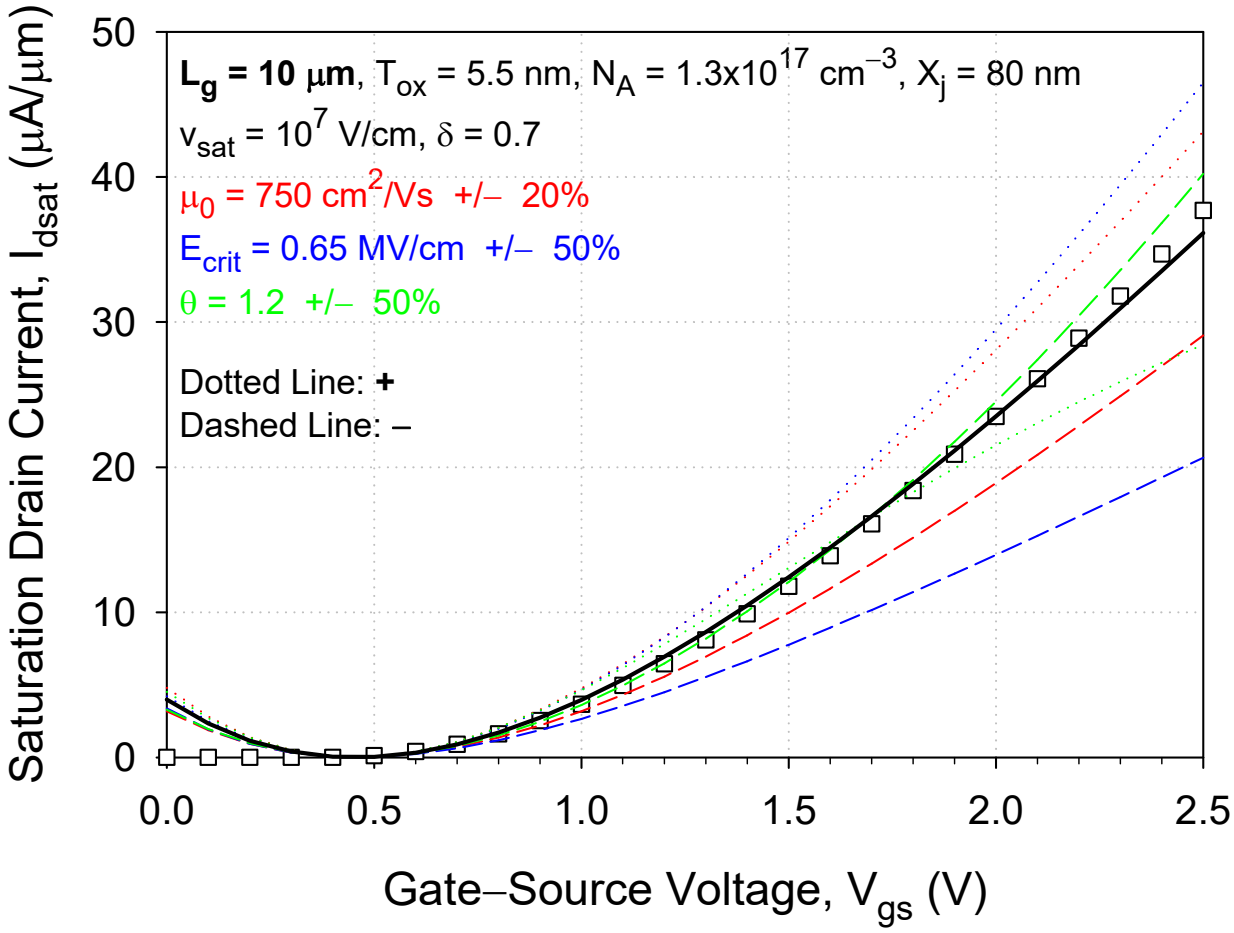
I_{ds} vs. V_{gs} at L_g = 10 μm for Parameter Extraction



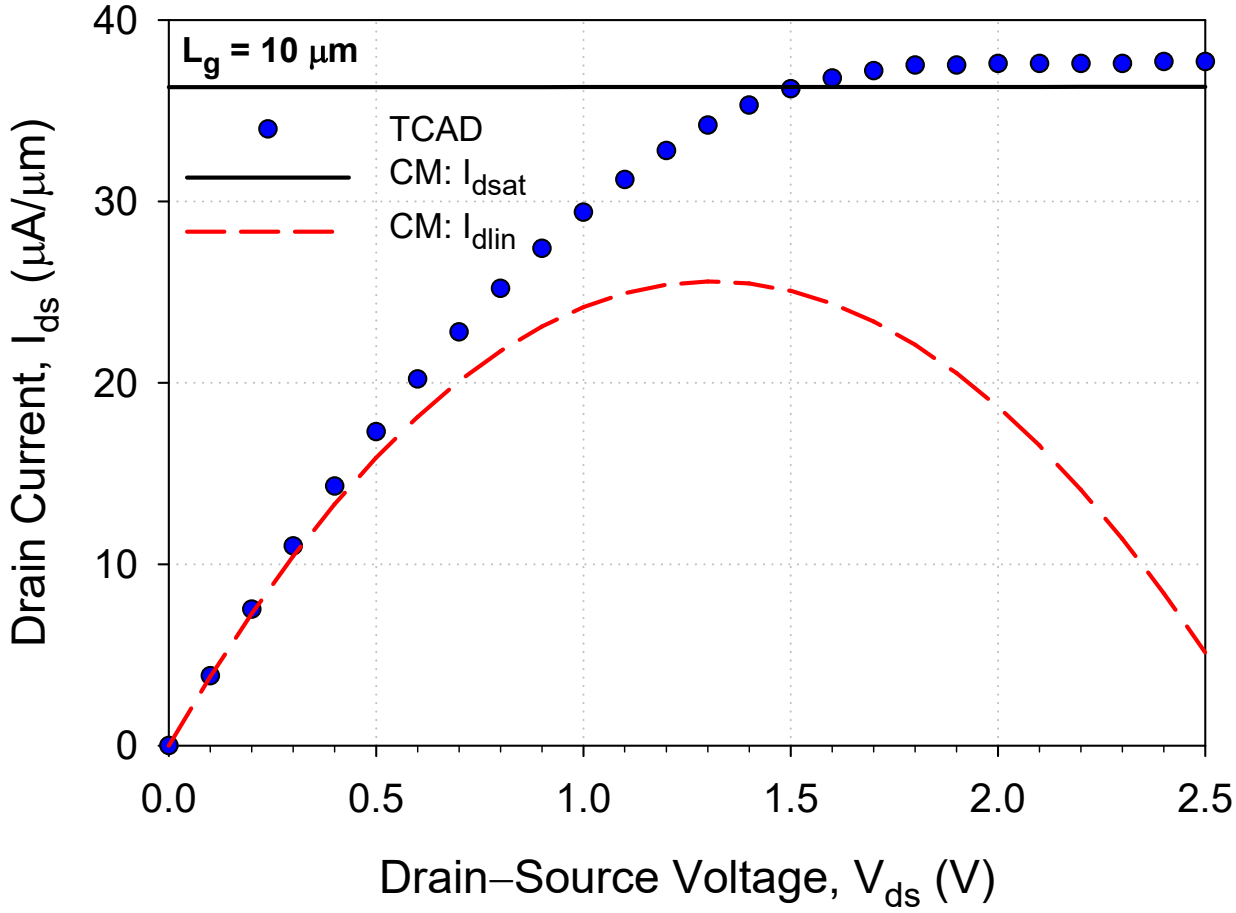
Parameter Variation Effect on I_{dlin} vs. V_{gs} at L_g = 10 μm



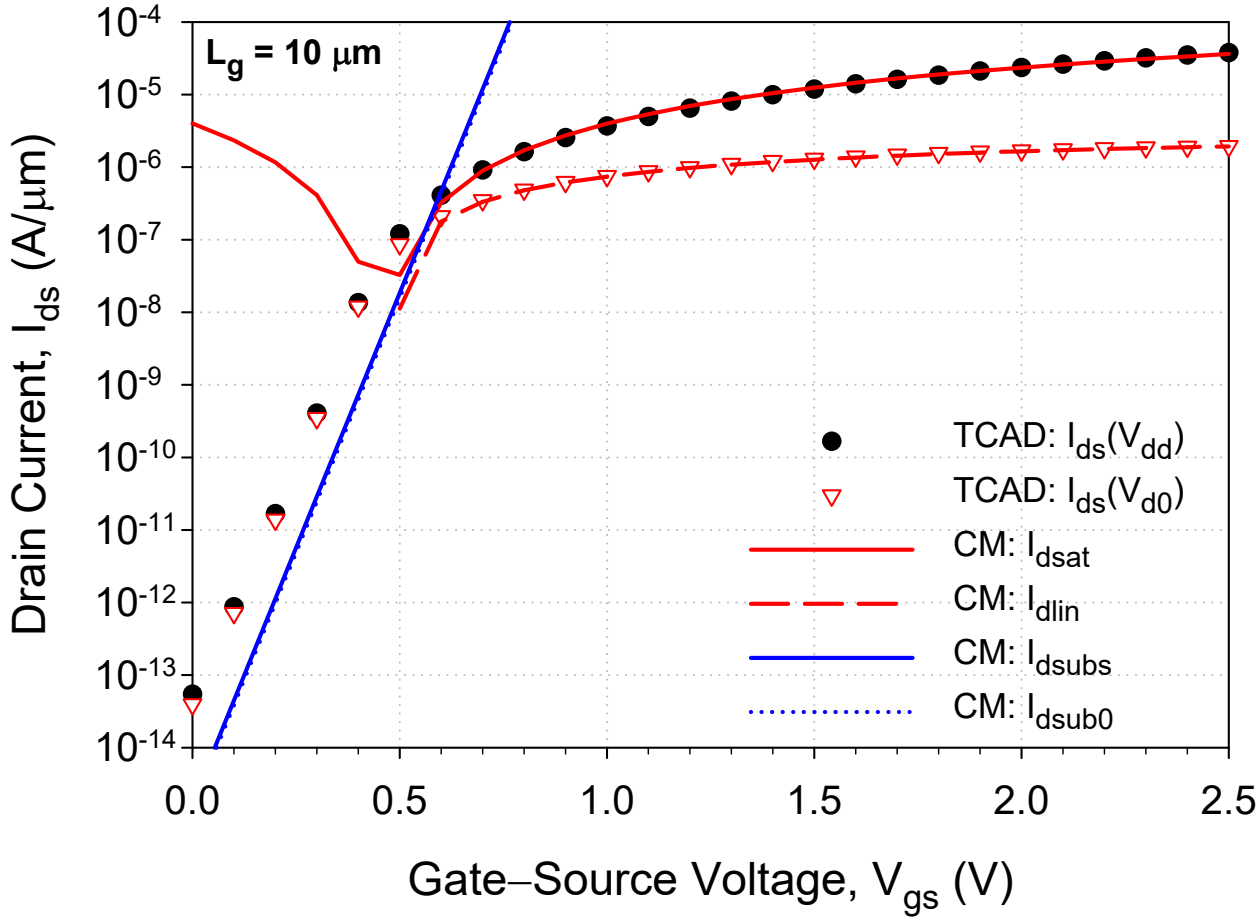
Parameter Variation Effect on I_{dsat} vs. V_{gs} at L_g = 10 μm



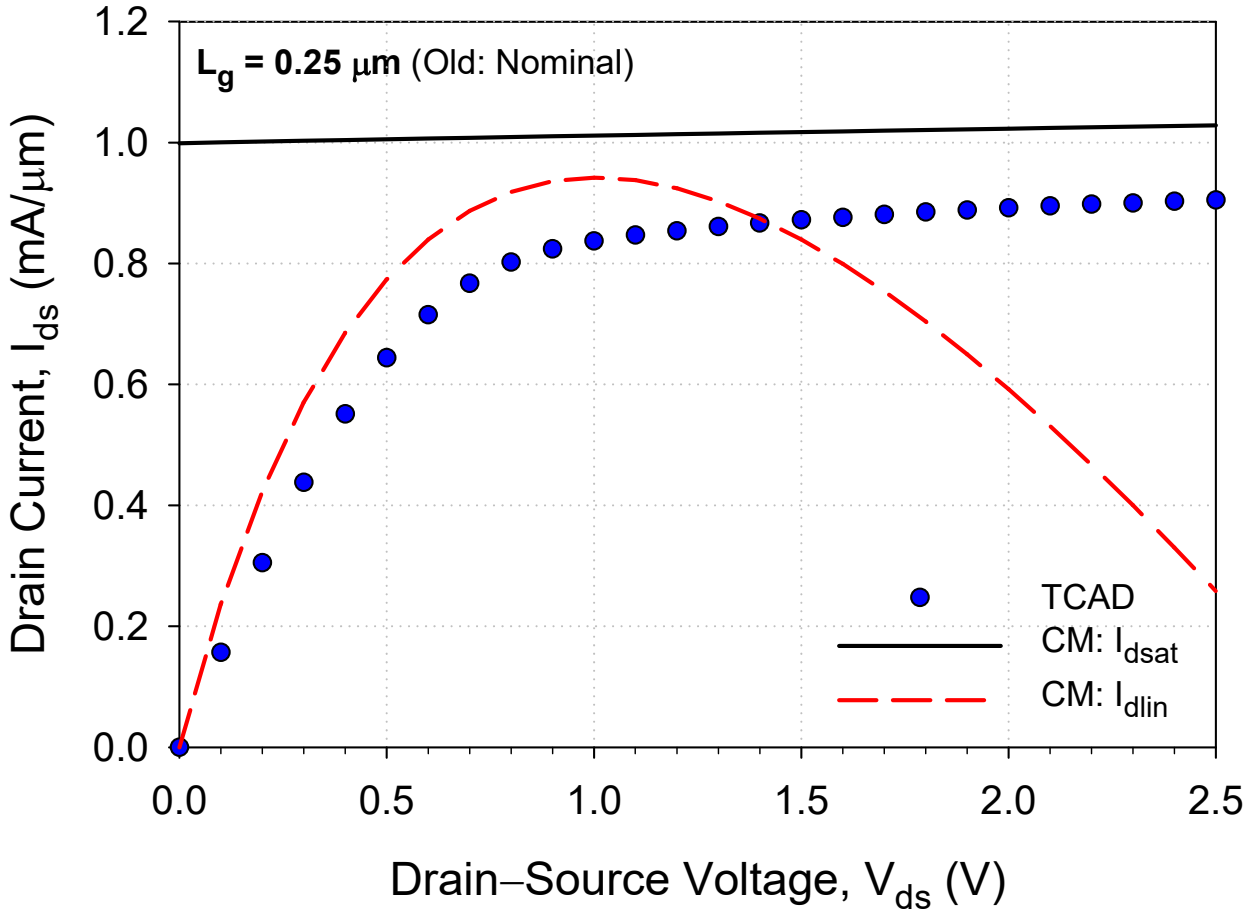
TCAD/CM: I_{ds} vs. V_{ds} at L_g = 10 μm



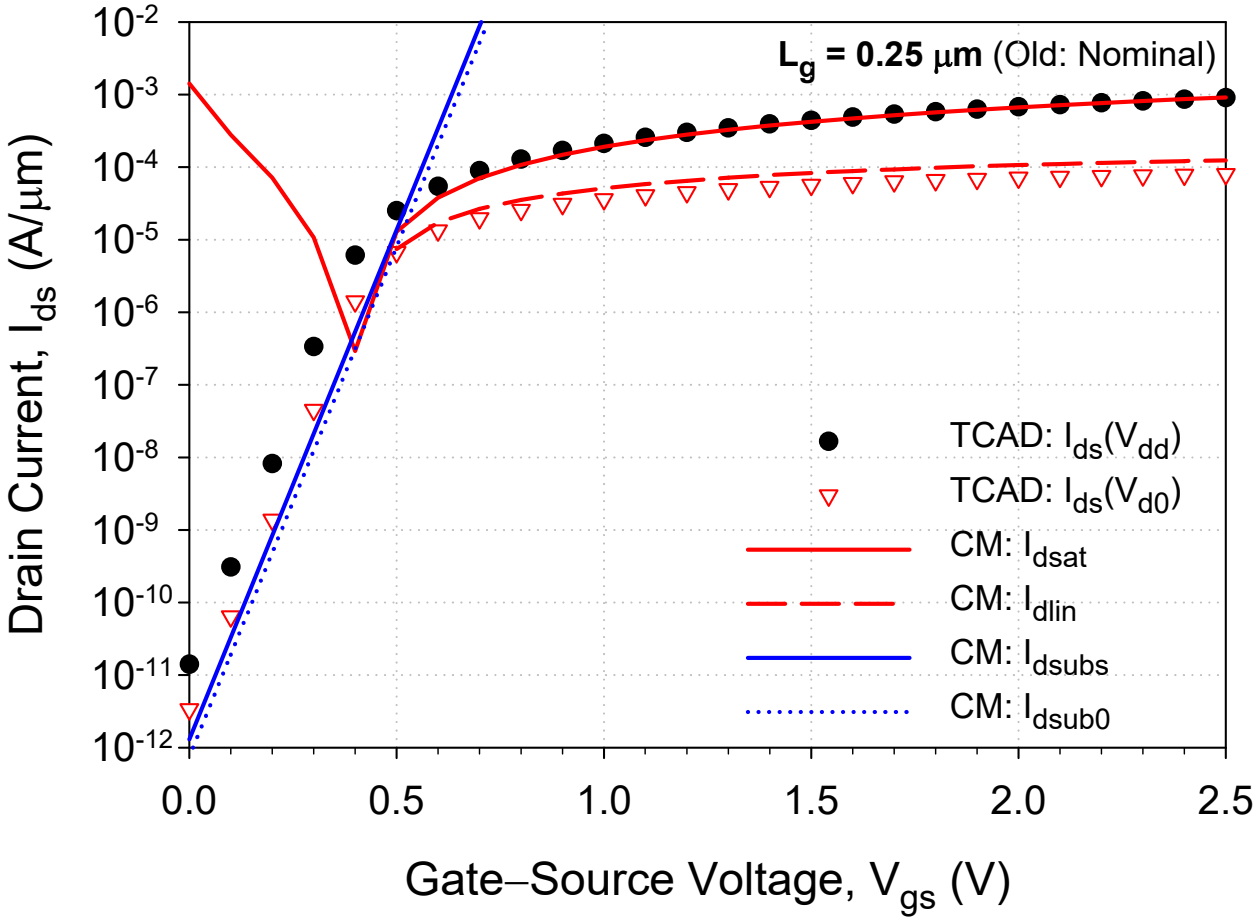
TCAD/CM: log(I_{ds}) vs. V_{gs} at L_g = 10 μm



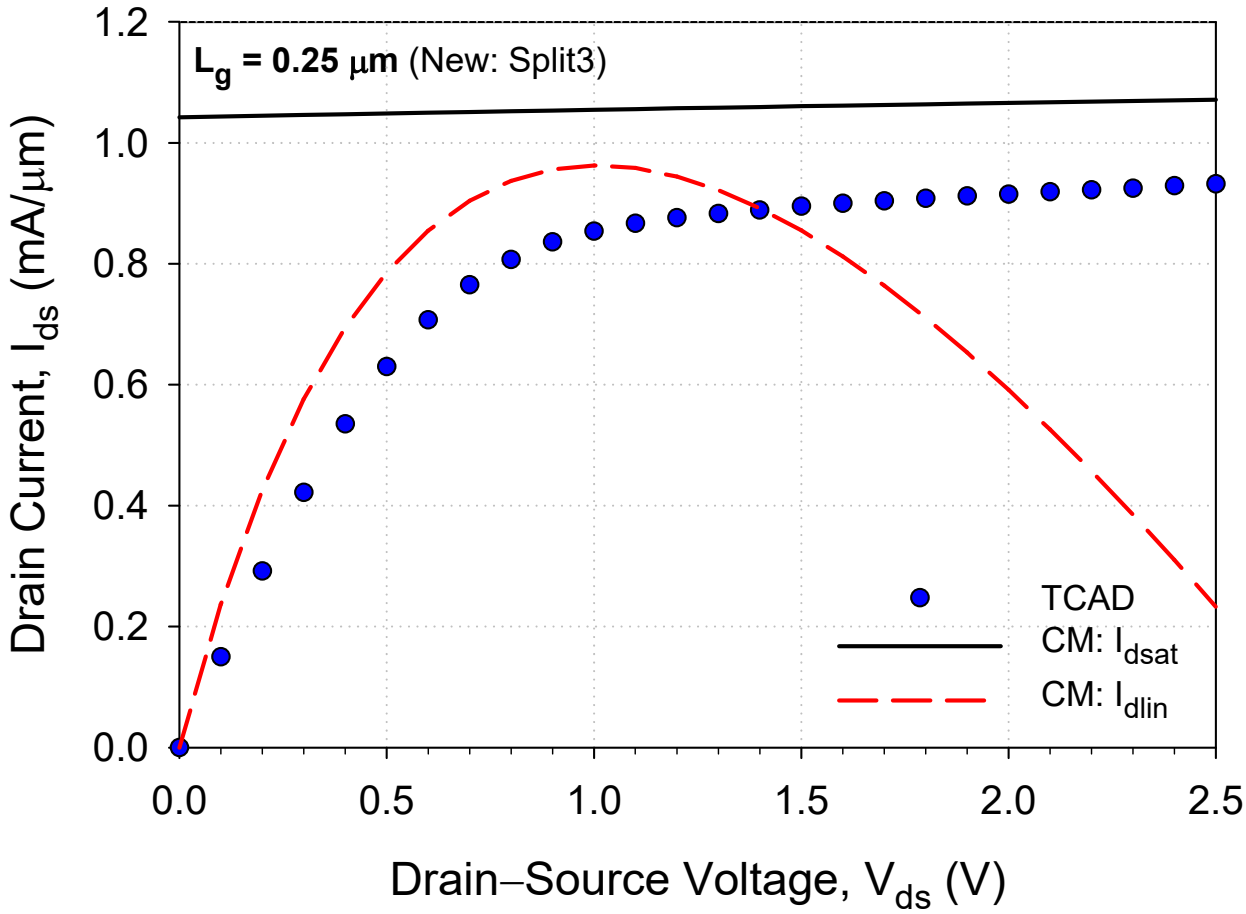
TCAD/CM: I_{ds} vs. V_{ds} at L_g = 0.25 μm (Nominal)



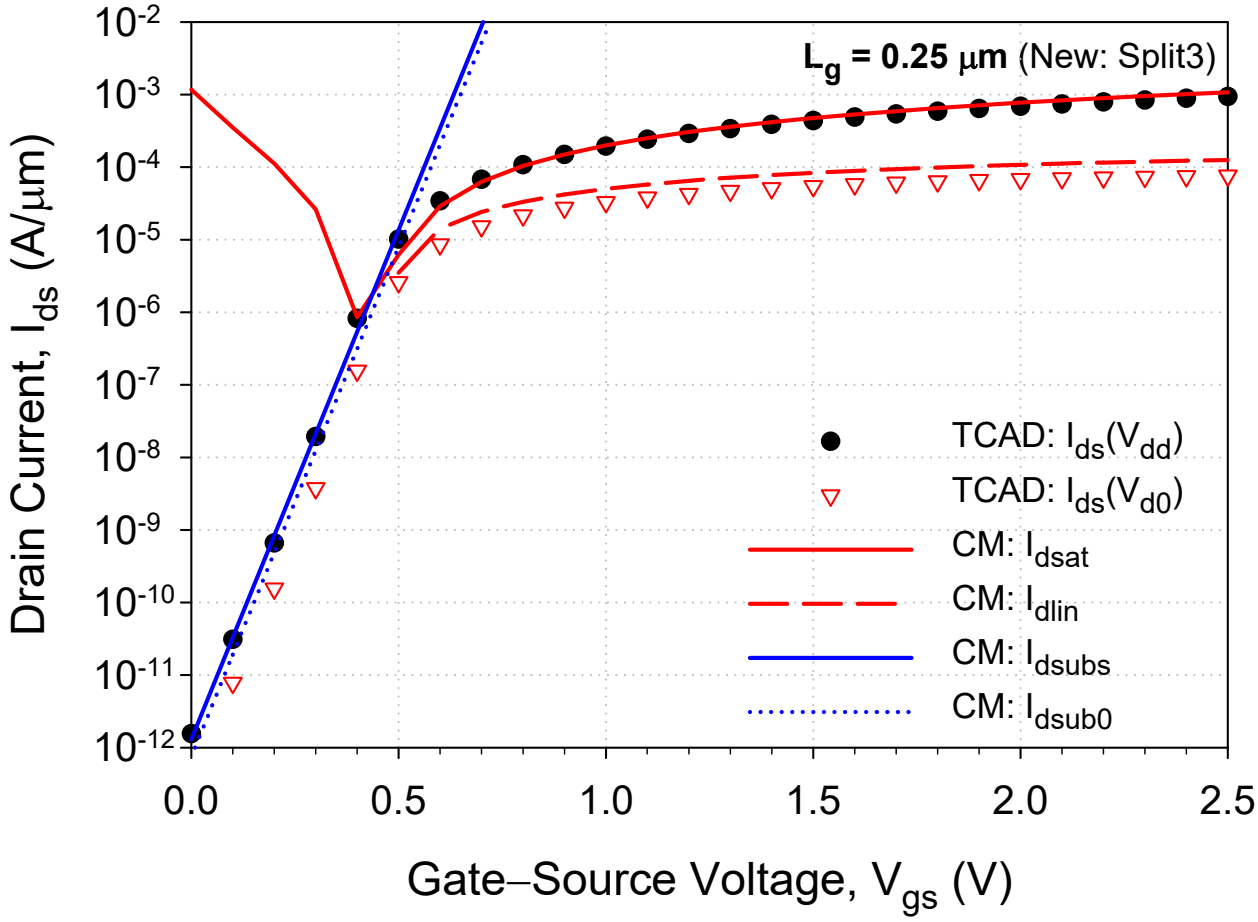
TCAD/CM: log(I_{ds}) vs. V_{gs} at L_g = 0.25 μm (Nominal)



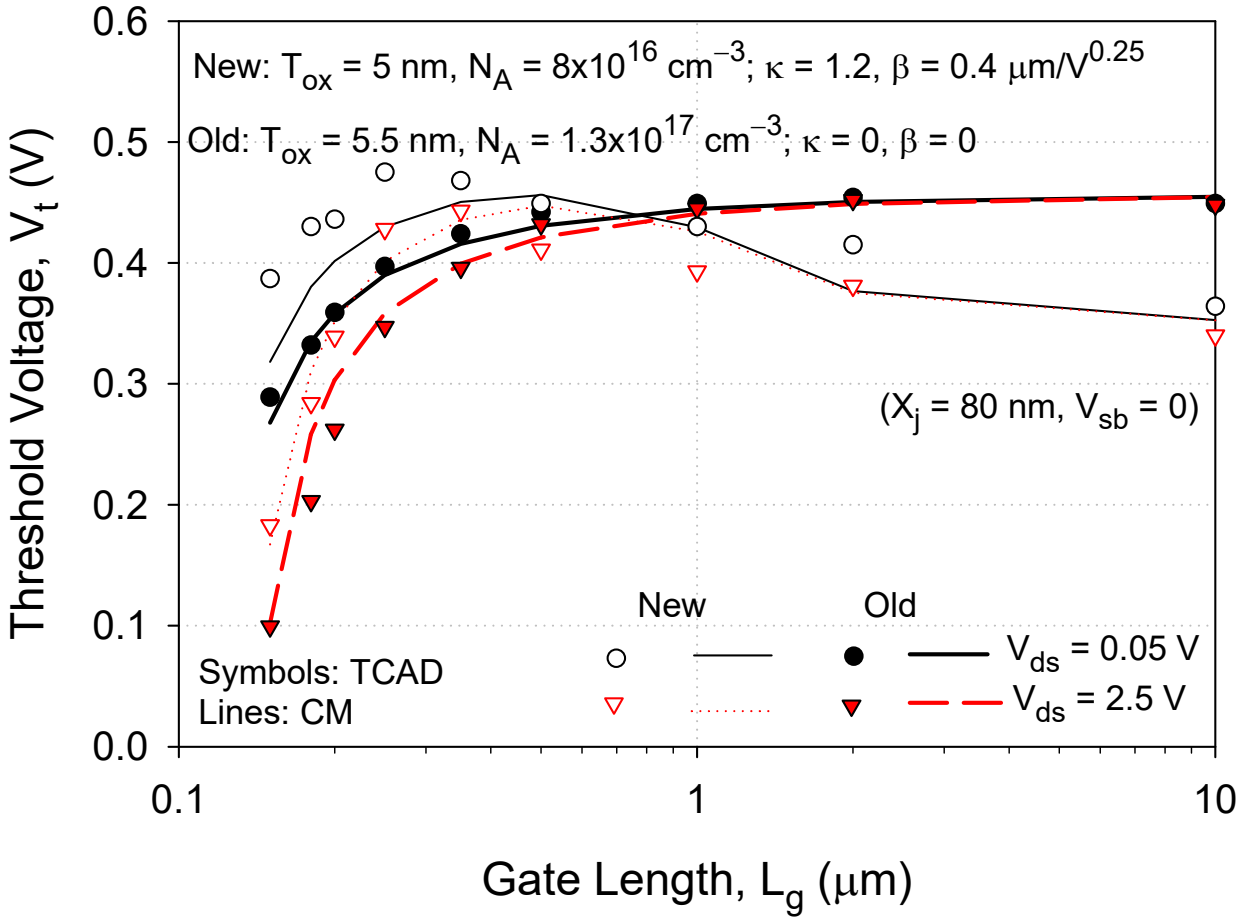
TCAD/CM: I_{ds} vs. V_{ds} at L_g = 0.25 μm (Split3)



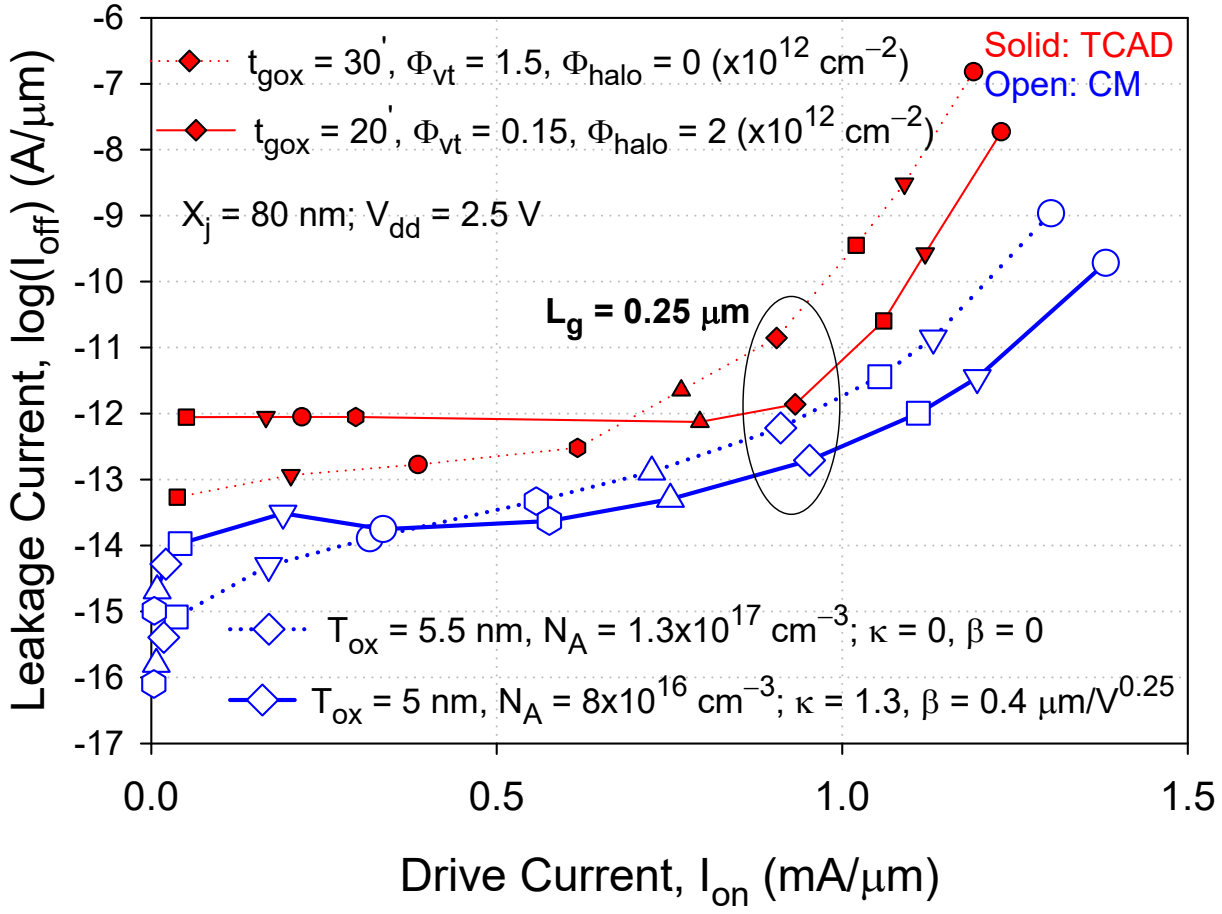
TCAD/CM: log(I_{ds}) vs. V_{gs} at L_g = 0.25 μm (Split3)



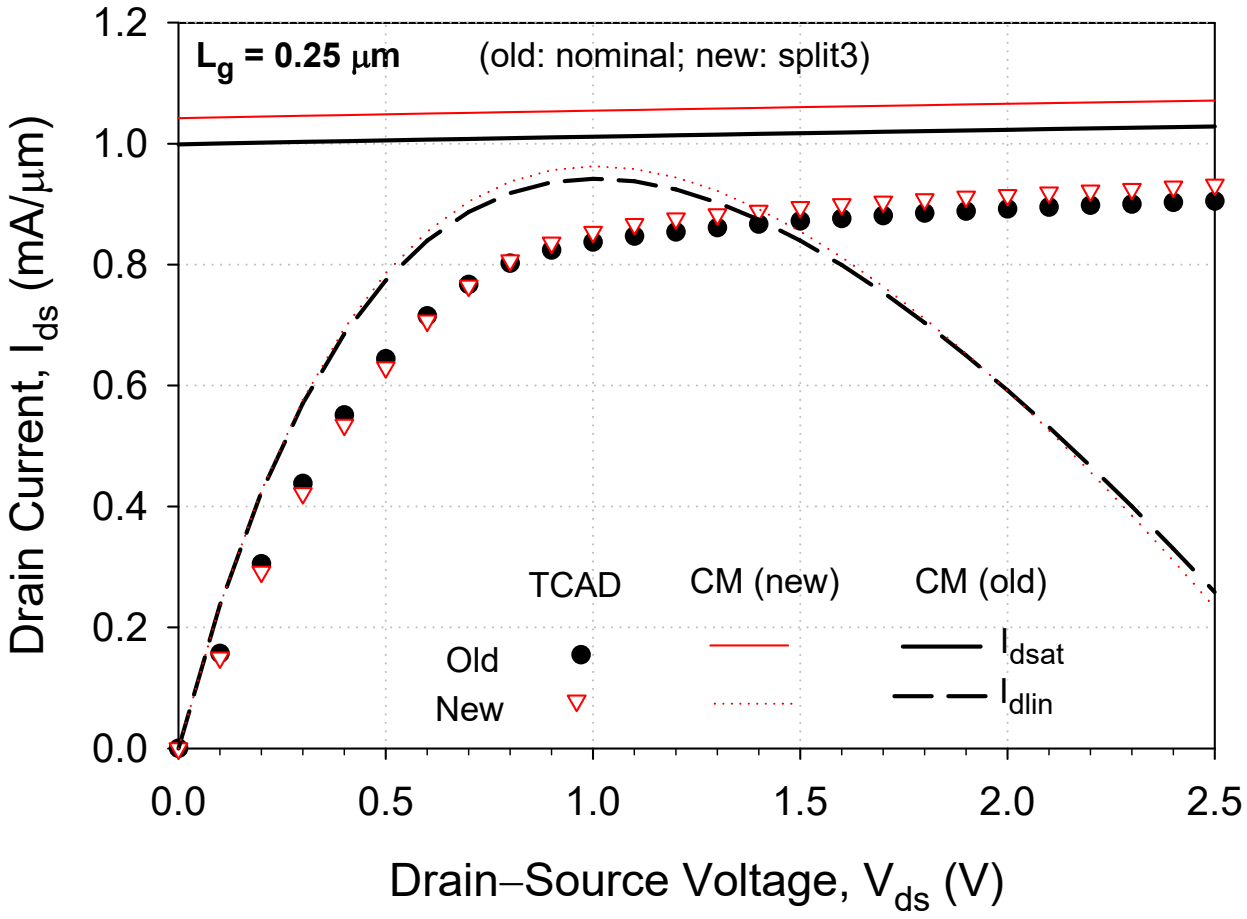
V_{t0} and V_{ts} vs. L_g for Old (Nominal) & New (Split3) Wafers



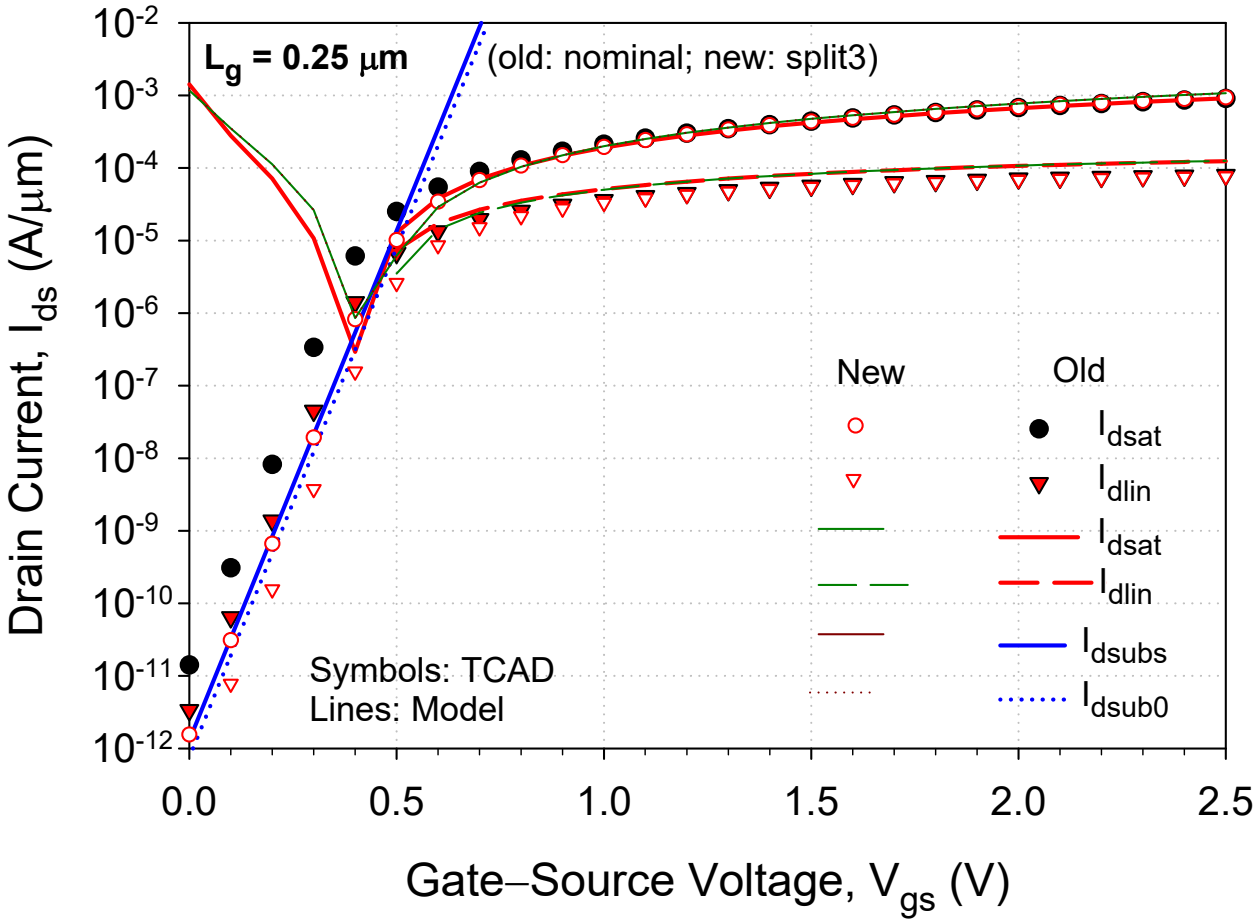
I_{off} vs. I_{on} at Various L_g for Old and New Wafers



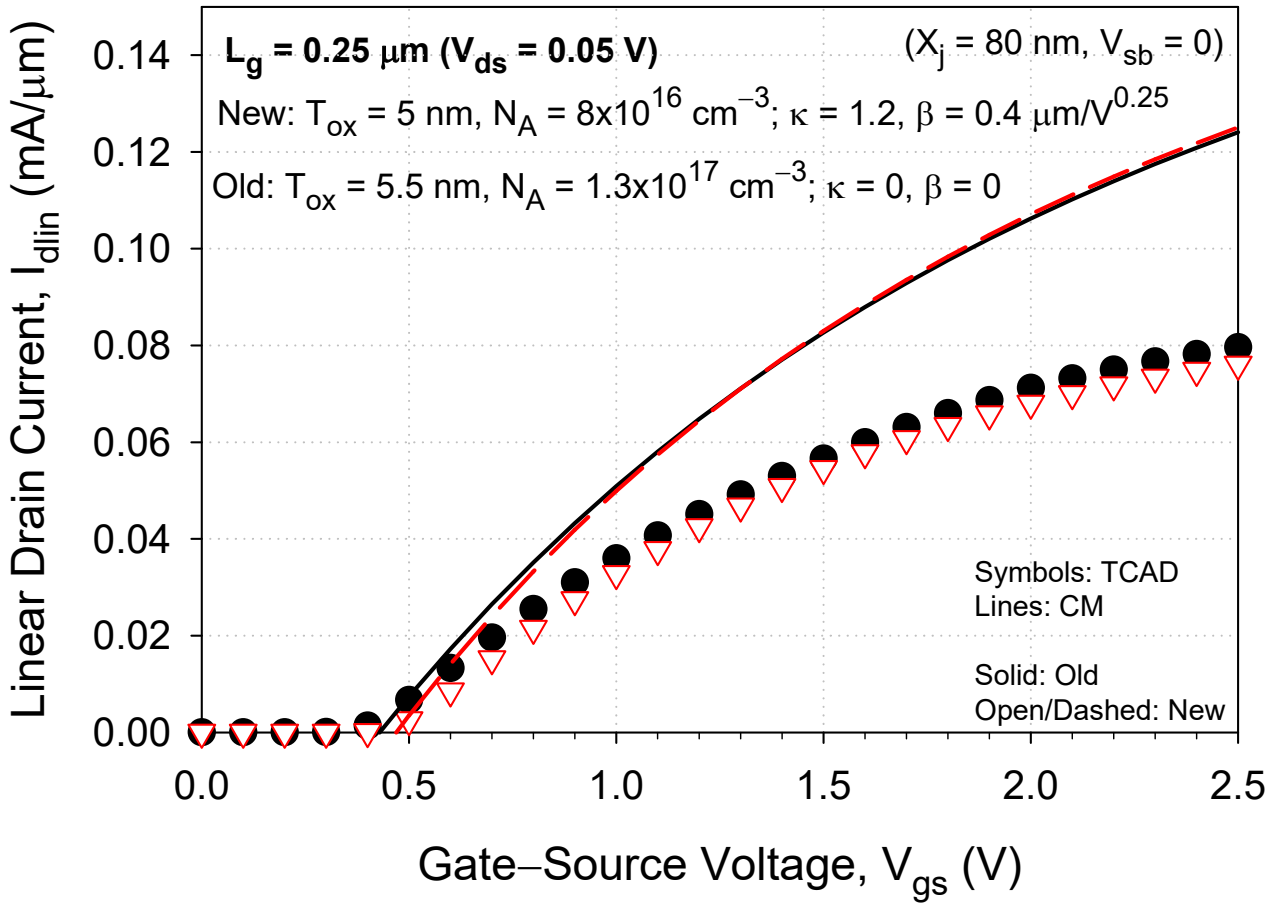
I_{ds} vs. V_{ds} at L_g = 0.25 μm for Old and New Wafers



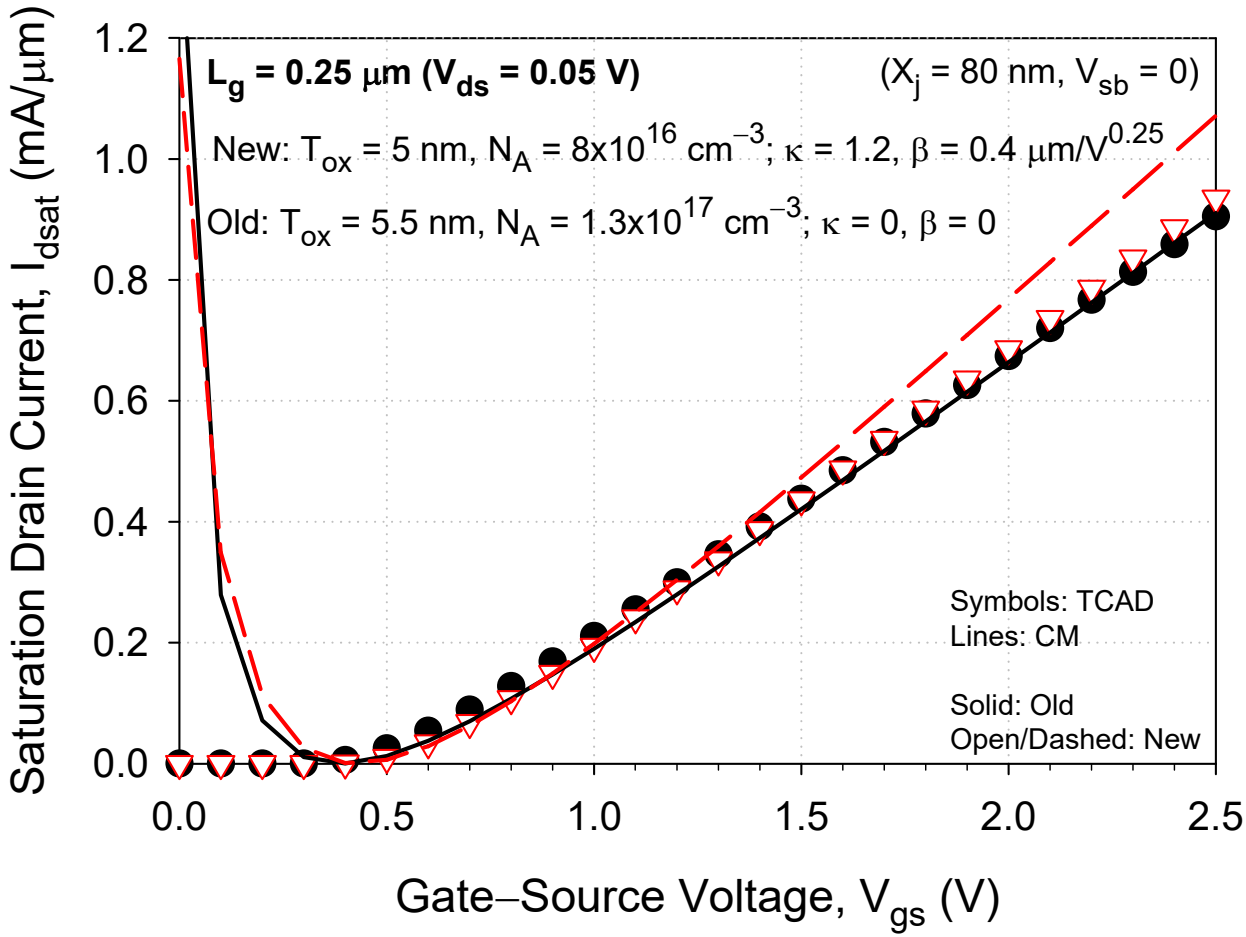
$\log(I_{ds})$ vs. V_{gs} at L_g = 0.25 μm for Old and New Wafers



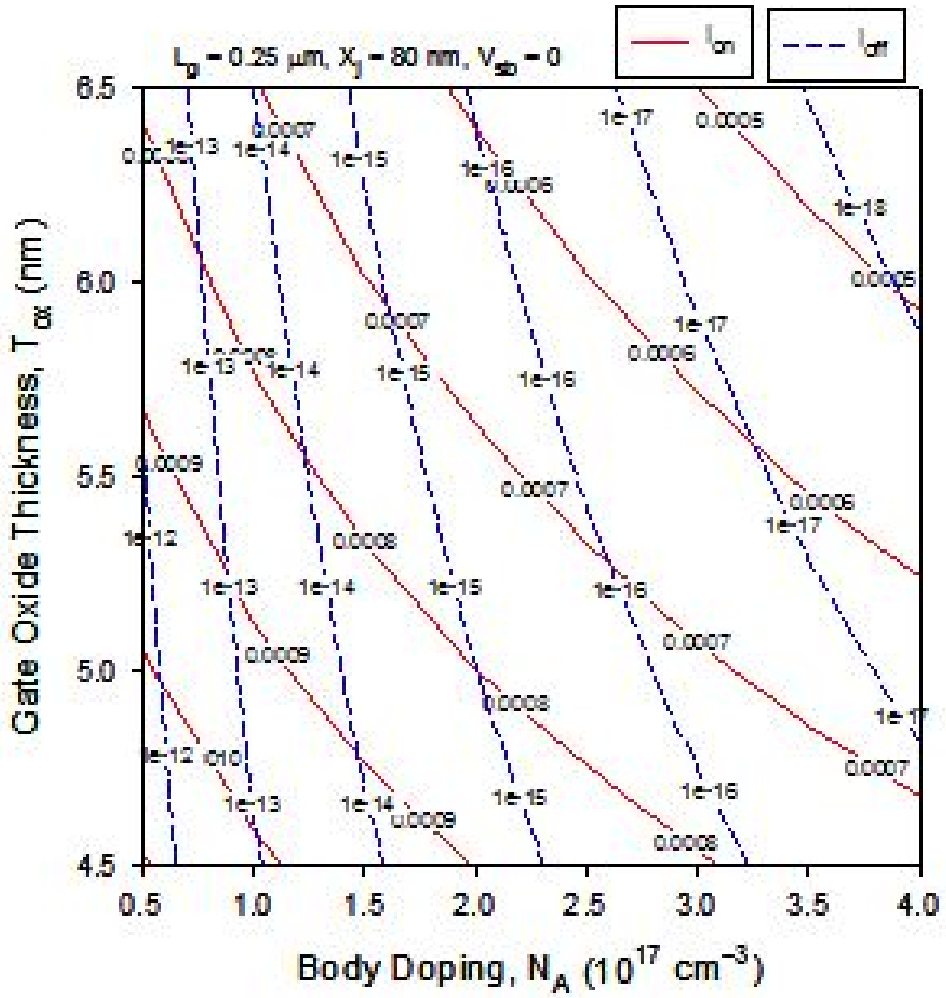
I_{dlin} vs. V_{gs} at L_g = 0.25 μm for Old and New Wafers



I_{dsat} vs. V_{gs} at L_g = 0.25 μm for Old and New Wafers



Contour Plot (Nominal): I_{on} and I_{off} vs. N_A and T_{ox}



Contour Plot (Nominal): I_{on}, I_{off}, and V_{ts} vs. N_A and T_{ox}